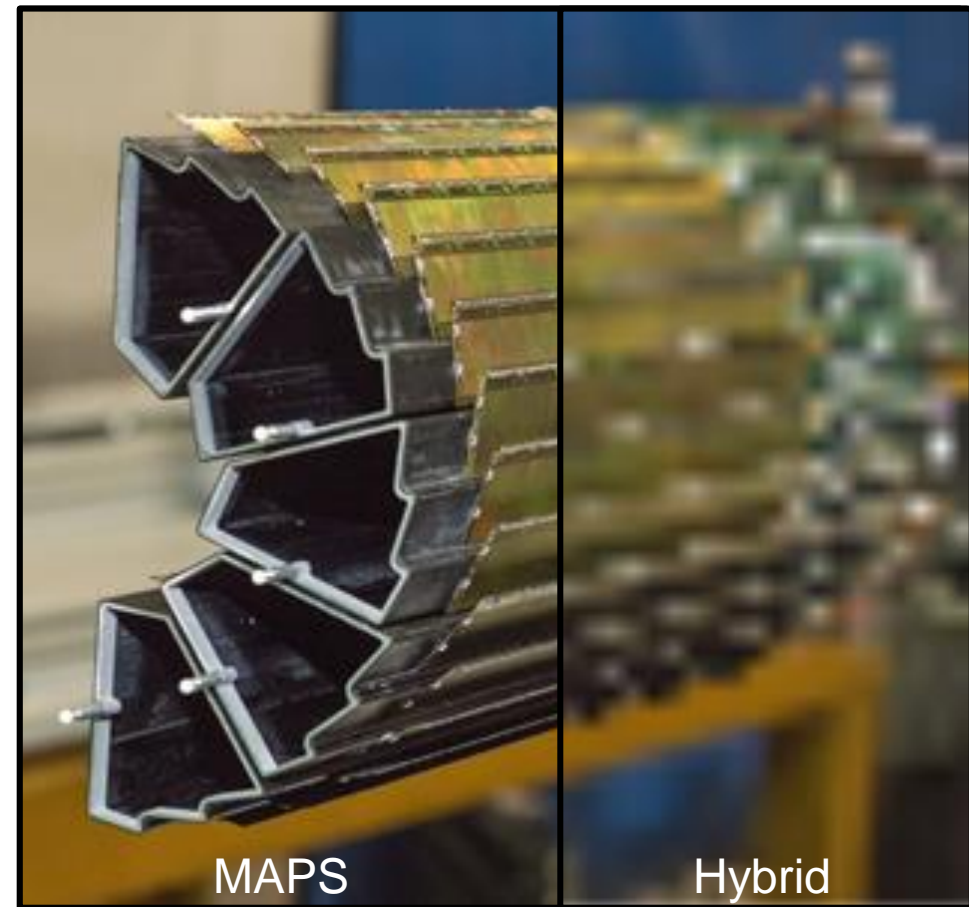
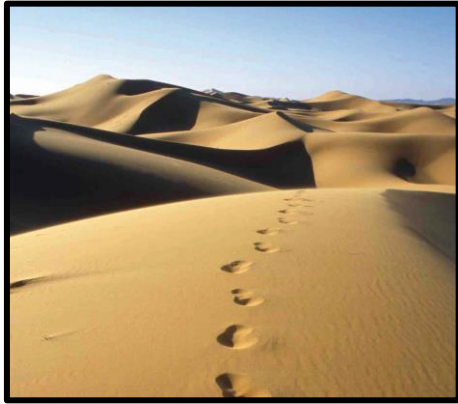


Silicon detectors IV

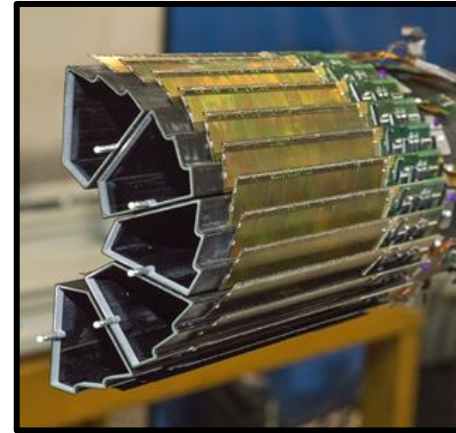
The rising of MAPS

M. Deveaux, GSI





+ ? =



1) Things you should know on silicon device production

2) CMOS Monolithic Active Pixel Sensors (MAPS)

Why MAPS are cool.

How not to collide the moon.

The struggle for radiation tolerance.

One chip is not enough.



What is required to build a particle detector?



Mostly a hammer...



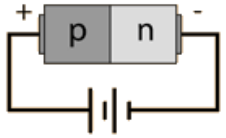
NA61/SHINE Small Acceptance Vertex Detector
Sum of 1000 pictures with ~100 heavy ion collisions.

Beam ion

Light particles



... a Webcam...



Width of the depleted zone:

$$w = \sqrt{\frac{2\epsilon_0\epsilon_r}{e} \left(\frac{1}{N_A} + \frac{1}{N_D} \right) U_{ext}}$$

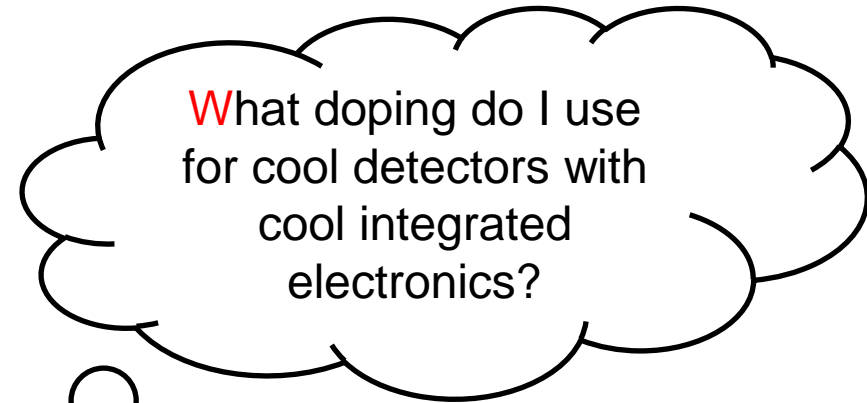
Break down voltage:

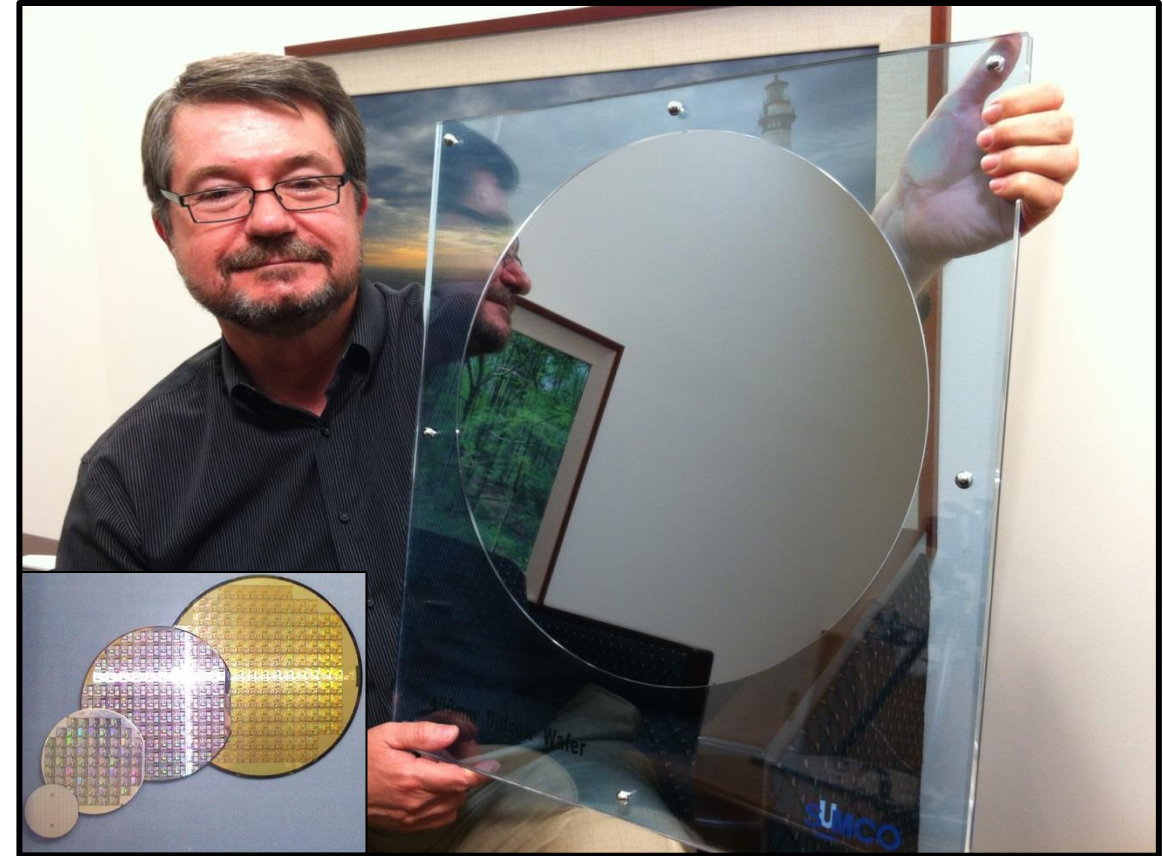
$$U_{max} = -\frac{1}{2} \frac{\epsilon_0\epsilon_r}{e} \left(\frac{1}{N_A} + \frac{1}{N_D} \right) E_{max}^2$$

Capacity of the diode:

$$C = A \cdot \frac{\epsilon_0\epsilon_r}{w}$$

Low doping: Cool detectors.
High doping: Cool electronics.





Silicon is melted into high purity mono-crystals.

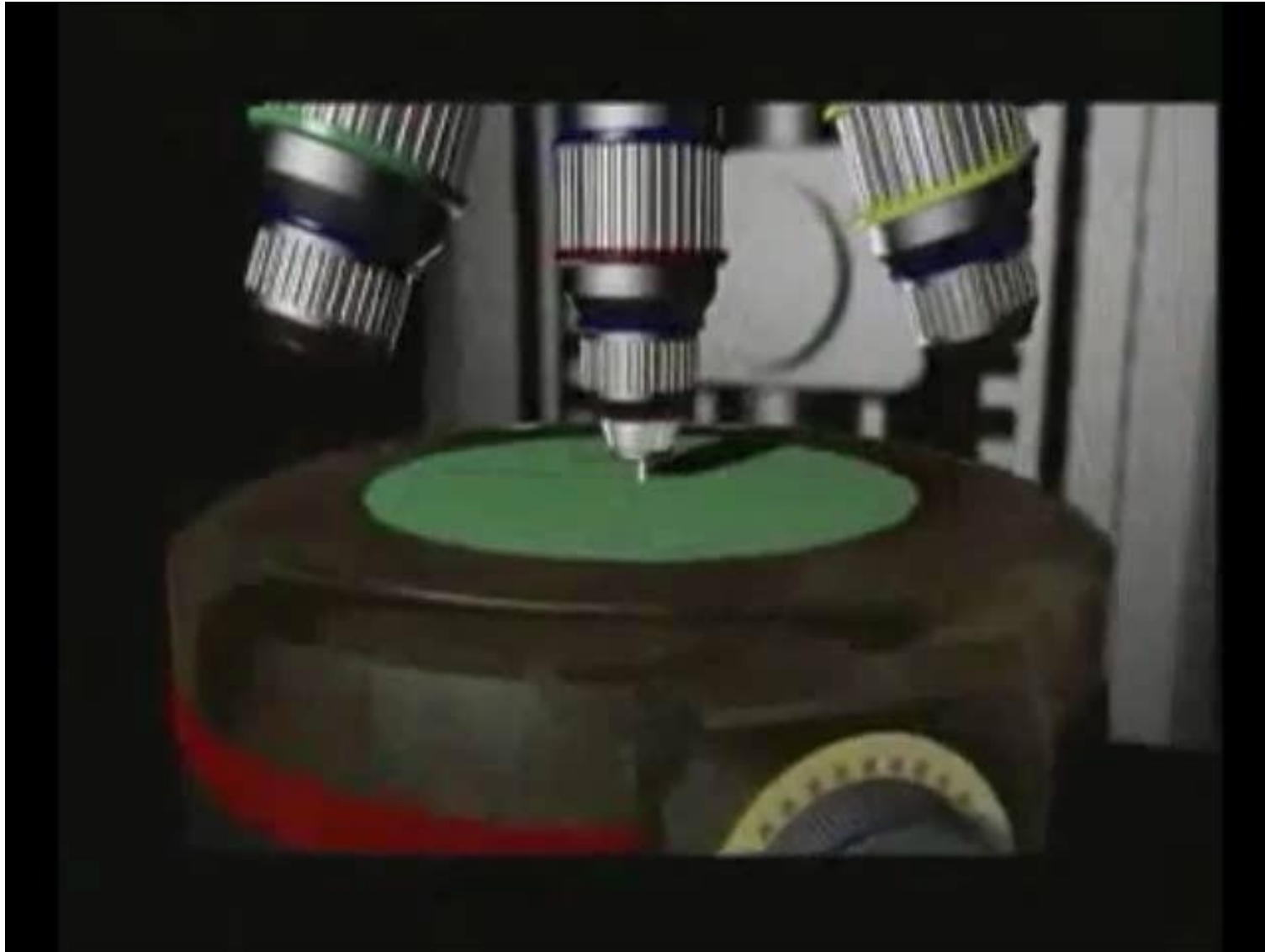
- Purity = cost
- Remaining impurities are controlled by doping.

⇒ All wafers are doped.

⇒ Low doping wafers are expensive.

⇒ Expensive stuff is rare industry (thus you don't get what you want).

Wafers exist in very different sizes, size matters.



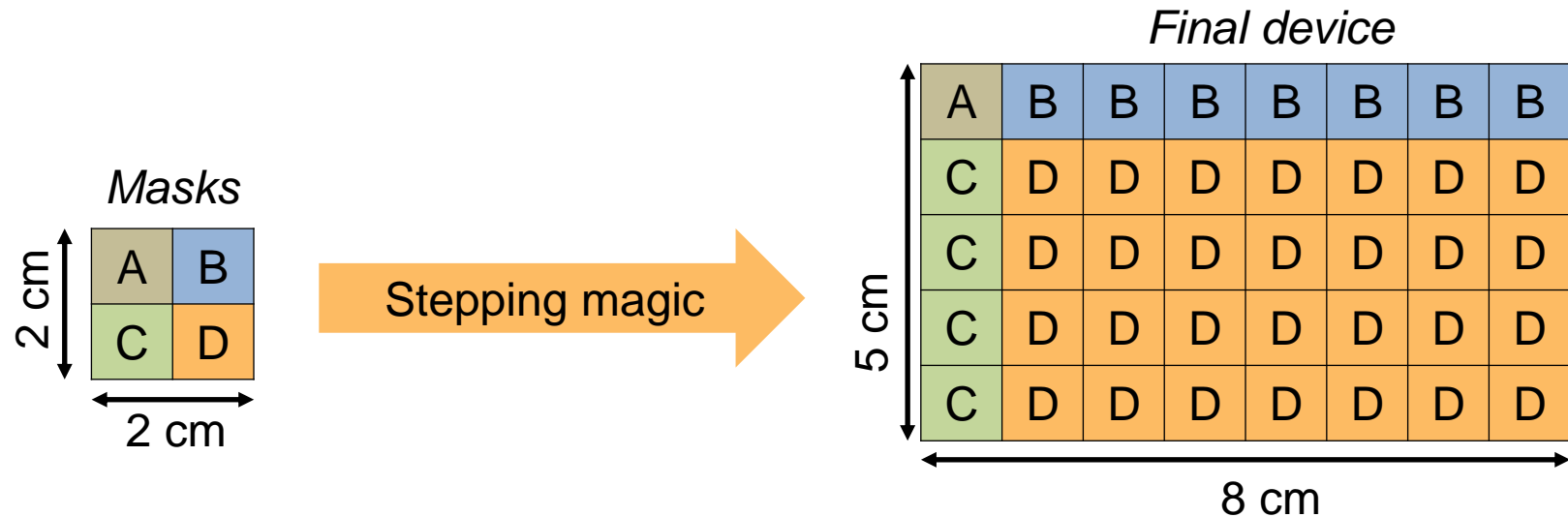
Minimum feature size (e.g. TJ 180 nm):

- Size of smallest structure on my realize with a process (typically transistor gate)
- Relevant sizes:
 - 5 nm (~50 atom layers) for modern digital electronics (e.g. smart phones).
 - 180 – 250 nm (detector electronics in production)
 - 28 – 65 nm (detector electronics under preparation)

Analog/radiation hard electronics:
A bit bigger is often better.

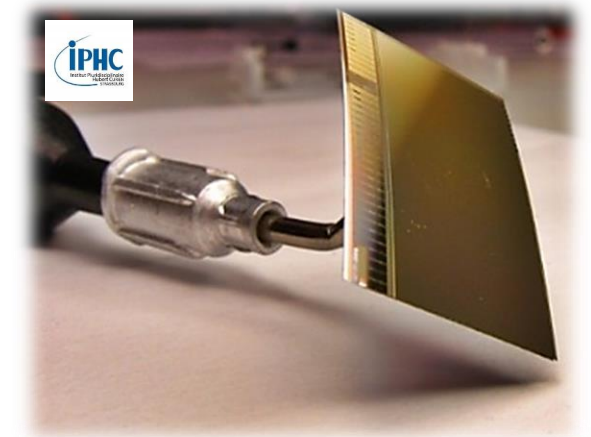
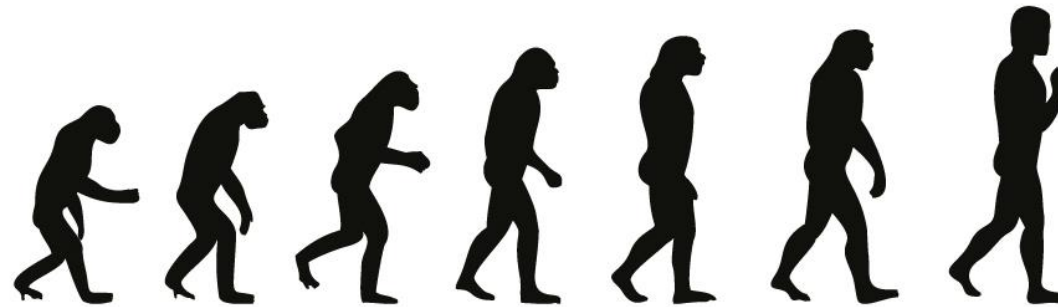
Reticle size: Biggest structure one can build with one lithography mask, typically ~3 x 2 cm².

Stitching: Build > reticle size devices by using repetitive structures





Geiger-counter (1932)

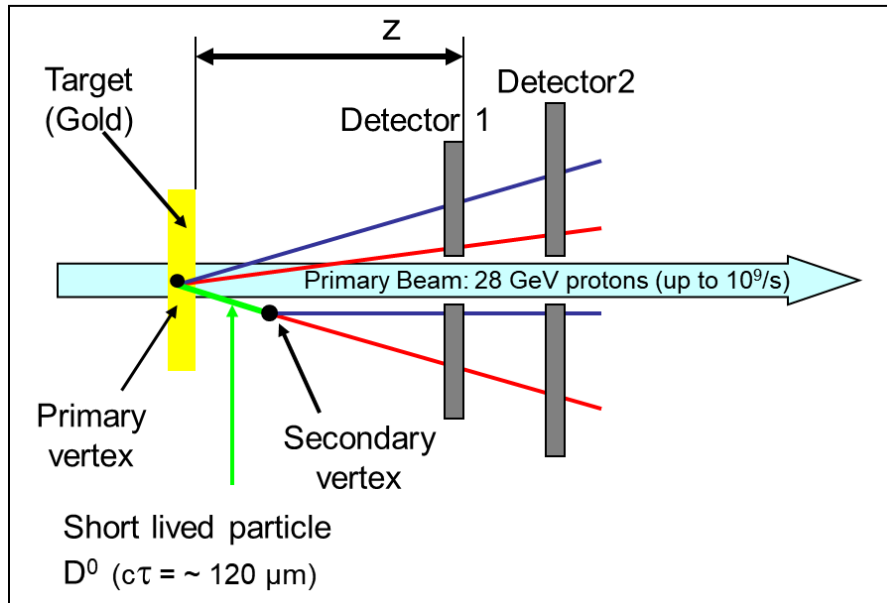


MAPS (nowadays)

Works for "stable" particles reaching the detectors.

What about less stable particles?

Open strange: $c\tau \approx 10$ mm, Open bottom: $c\tau \approx 1$ mm, Open Charm: $c\tau \approx 0.1$ mm



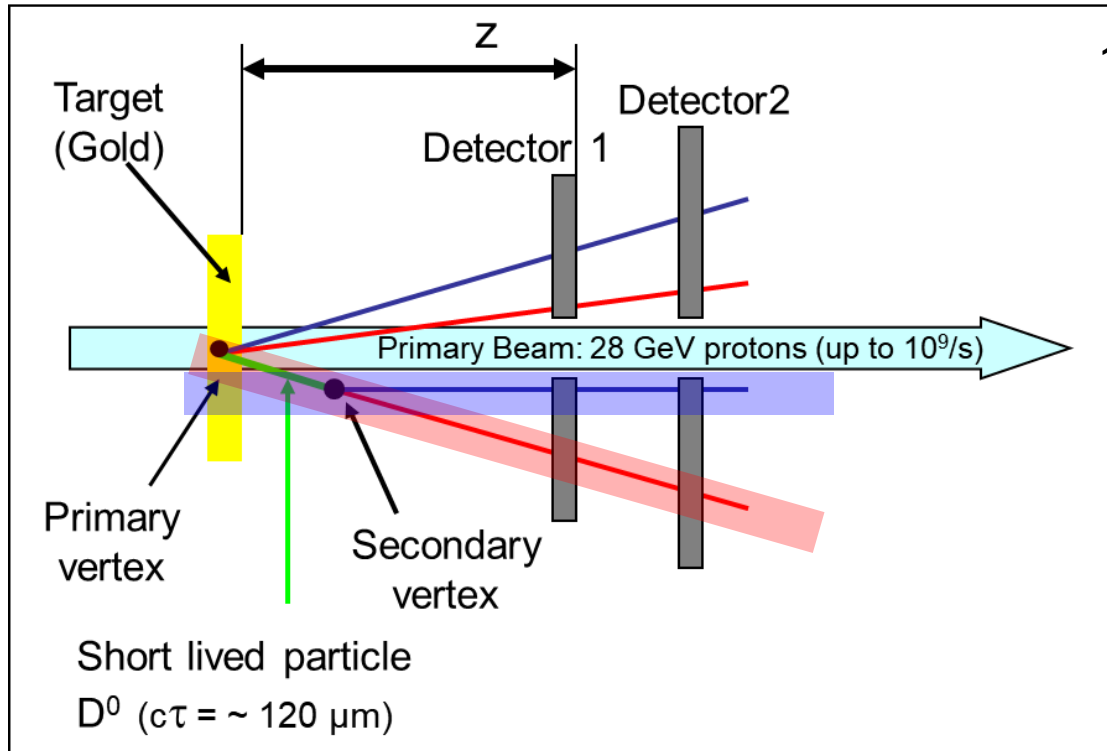
Prove existence of short lived particle by separating primary and secondary vertex.

Compute its properties by:

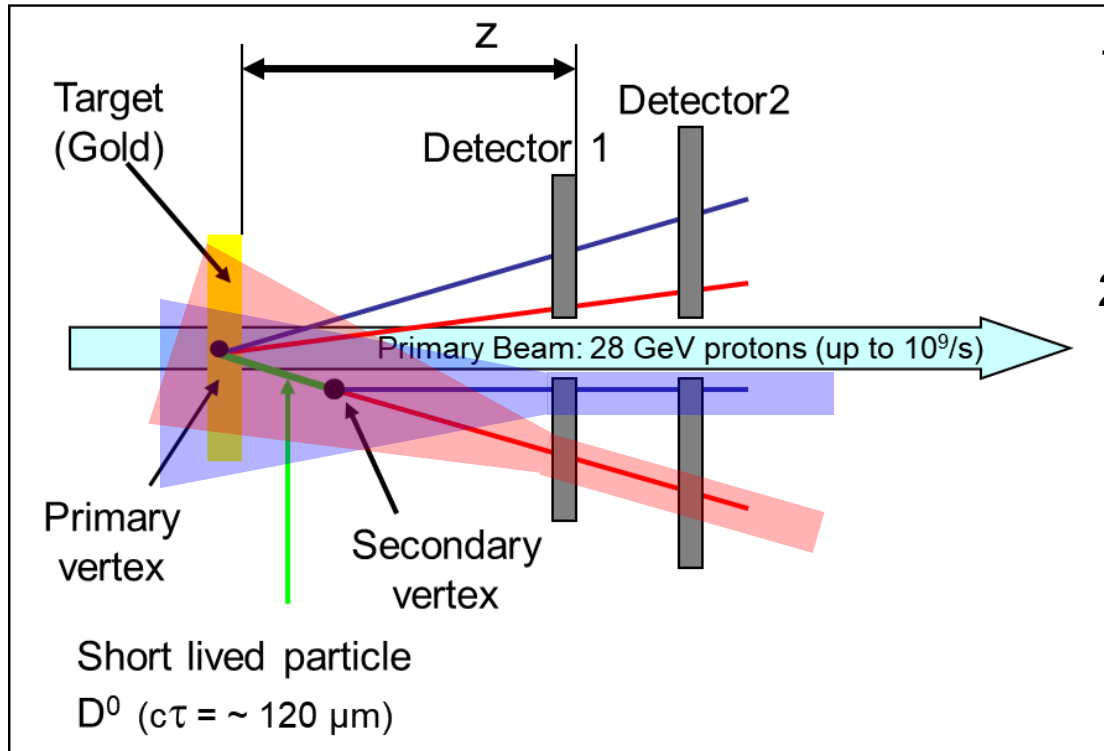
- Adding 4-vectors of daughters (invariant mass).
- "Add" quark content of daughters.

Sounds too easy, where is the challenge?



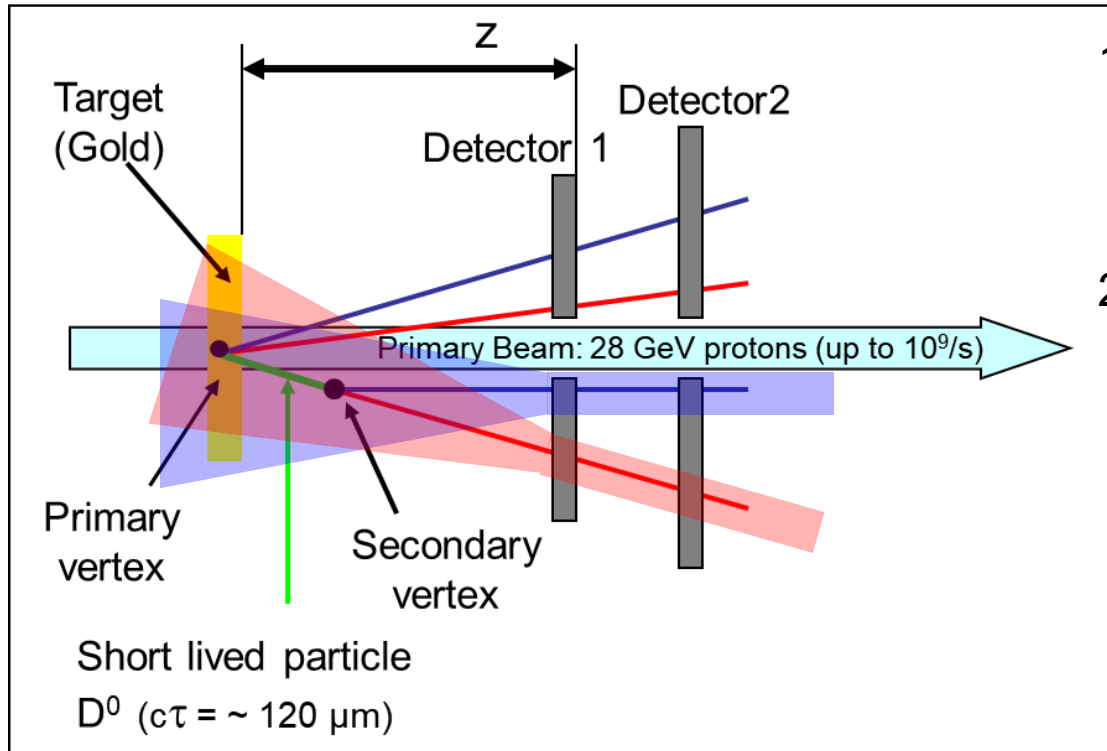


1. Limited detector resolution spoils vertex resolution.
 - Needs $<5\mu m$.



1. Limited detector resolution spoils vertex resolution.
 - Needs $< 5 \mu m$.
2. Multiple coulomb scattering manipulated particle trajectory.
 - Needs $x < 0.3\% X_0$.

Radiation length



1. Limited detector resolution spoils vertex resolution.
 - Needs $< 5\mu\text{m}$.
2. Multiple coulomb scattering manipulated particle trajectory.
 - Needs $x < 0.3\% X_0$.

300 μm Si

Radiation length

$\frac{x}{X_0}$ - Material budget.
1% $X_0 \approx 1 \text{ mm Si}$.
Data in PDG-booklet

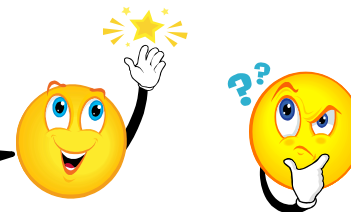
Scattering angle

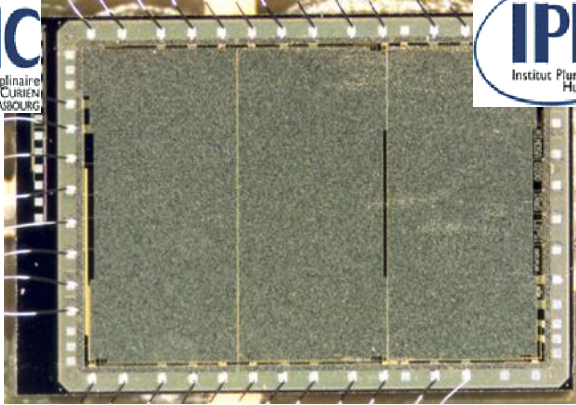
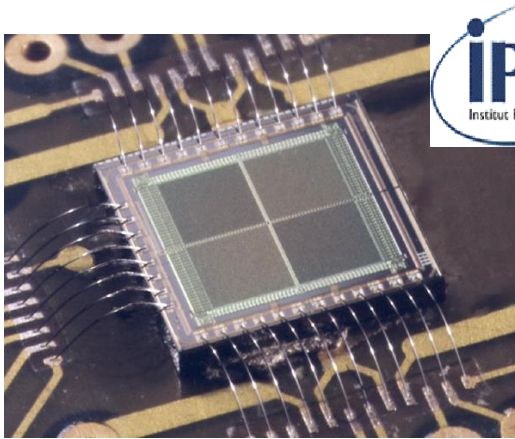
Relativistic particles with $z=1$

$$\Theta = \frac{13.6 \text{ MeV}}{\beta c p} \cdot z \cdot \sqrt{\frac{x}{X_0}} \cdot \left[1 + 0.038 \log\left(\frac{x}{X_0}\right) \right]$$

No challenge...

We just have to build mass-less detectors with infinitely good spatial resolution and perfect efficiency...

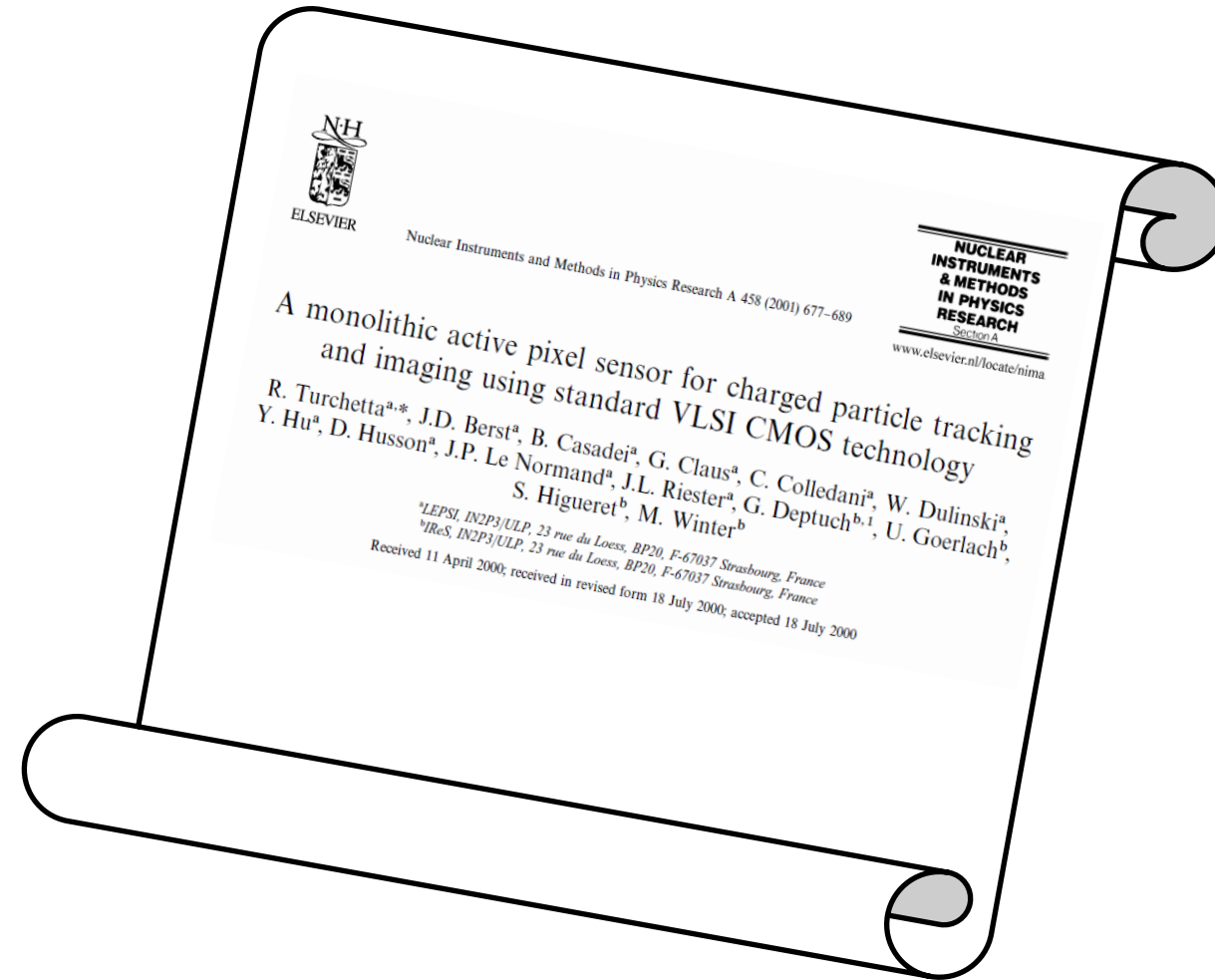




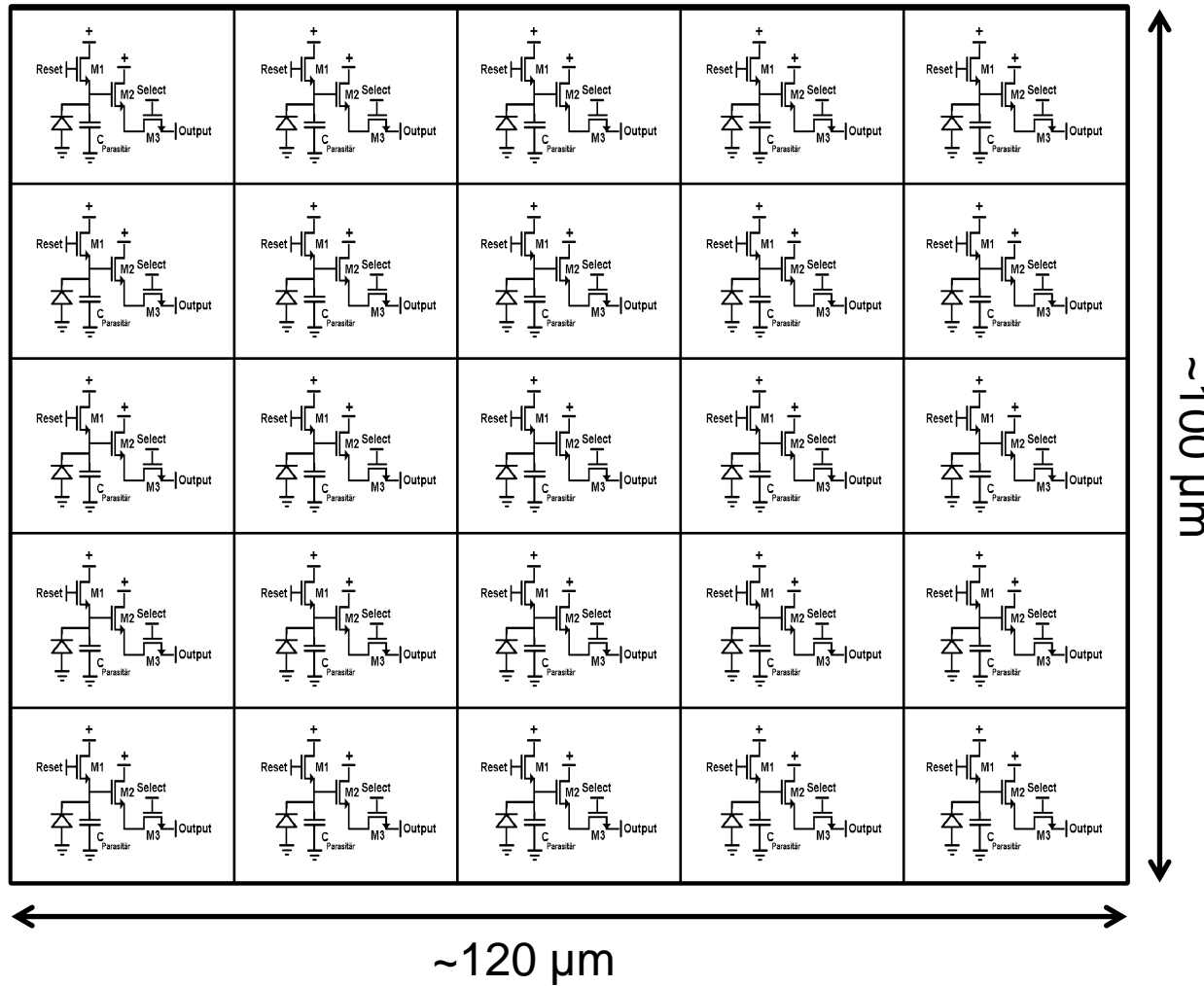
MIMOSA – 1 (1999)

MIMOSA – 1 (2000)

	Mi - 1
Pixel size [μm^2]	20 x 20
Pixel number	N x 64 x 64
Readout	Analog
Frame time [μs]	$\sim 10^4$
Dead time	> 50%

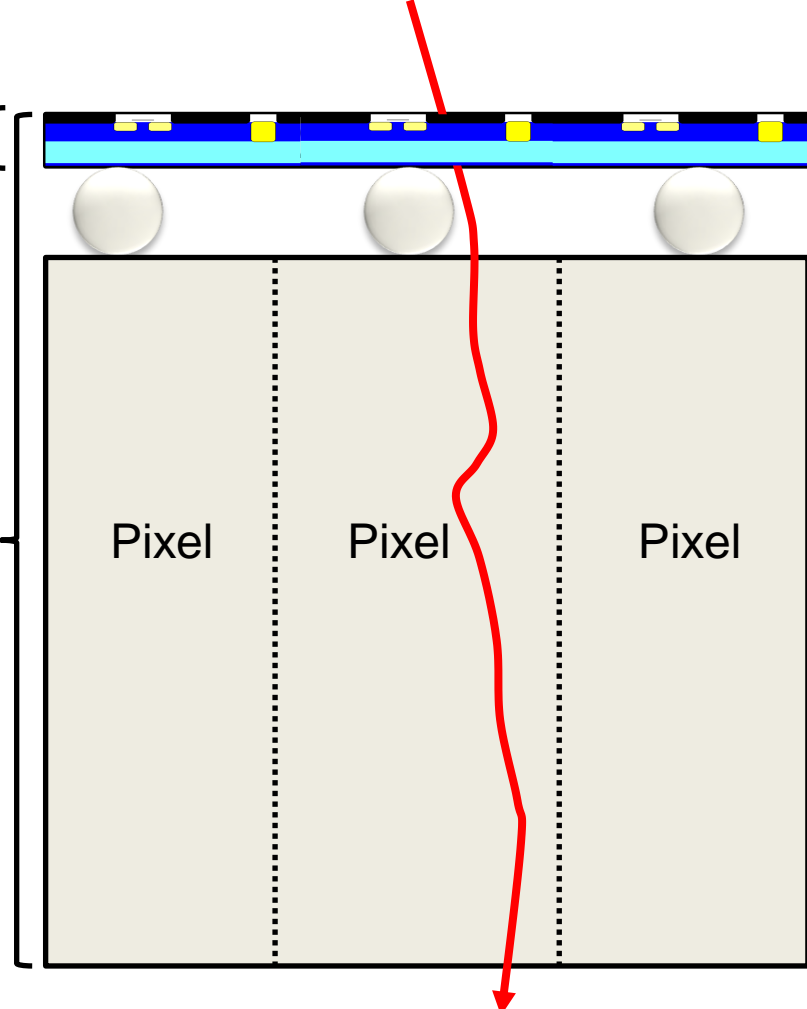


CMS @ LHC – Hybrid Pixel

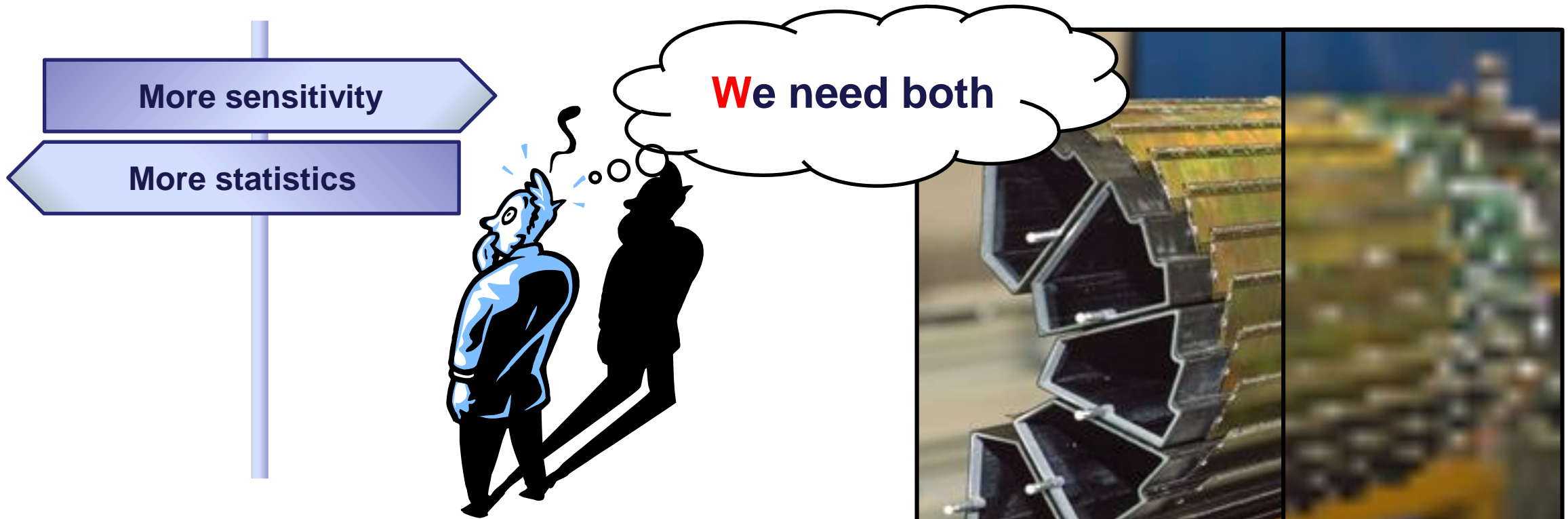


MAPS:
~0.05 μm
Si equivalent

Hybrid:
0.5mm Si
equivalent

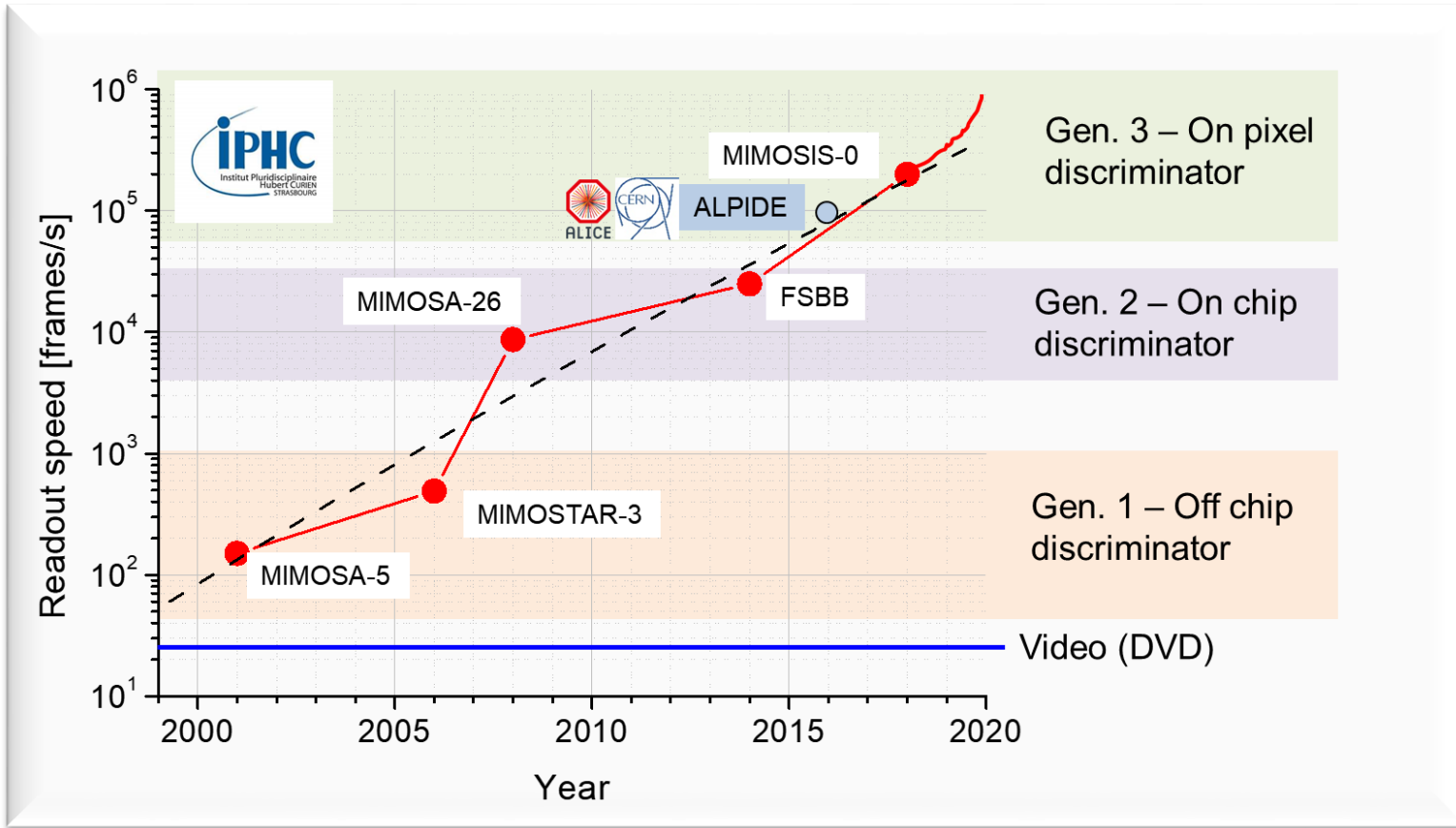


Multiple coulomb scattering:
Particle trajectory is manipulated by detector.
Angle scales with $\sqrt{\text{thickness}} / p$



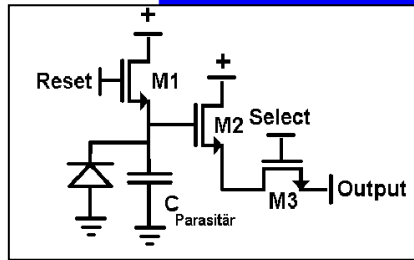
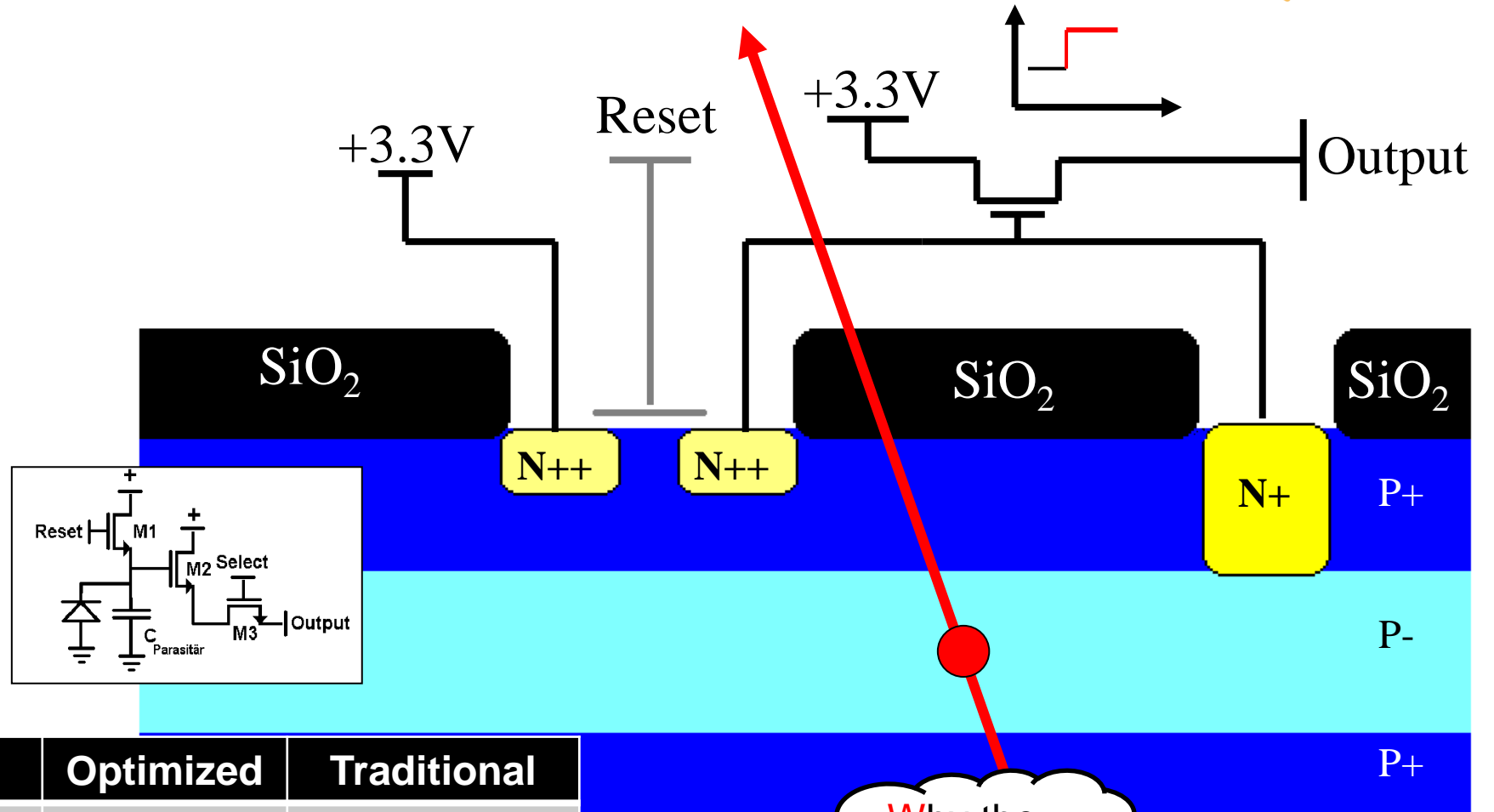
	Hybrid pixels (2001)	MAPS (2001)
Single point resolution	~ 30 μm	~2 μm
Material budget	~ 500 μm Si	~ 50 μm Si

MAPS show charge sharing:
 $\sigma \approx p/10$ (analog readout)
 $\sigma \approx p/10$ (digital readout)



Time resolution?
Particle rate?
Data bandwidth?



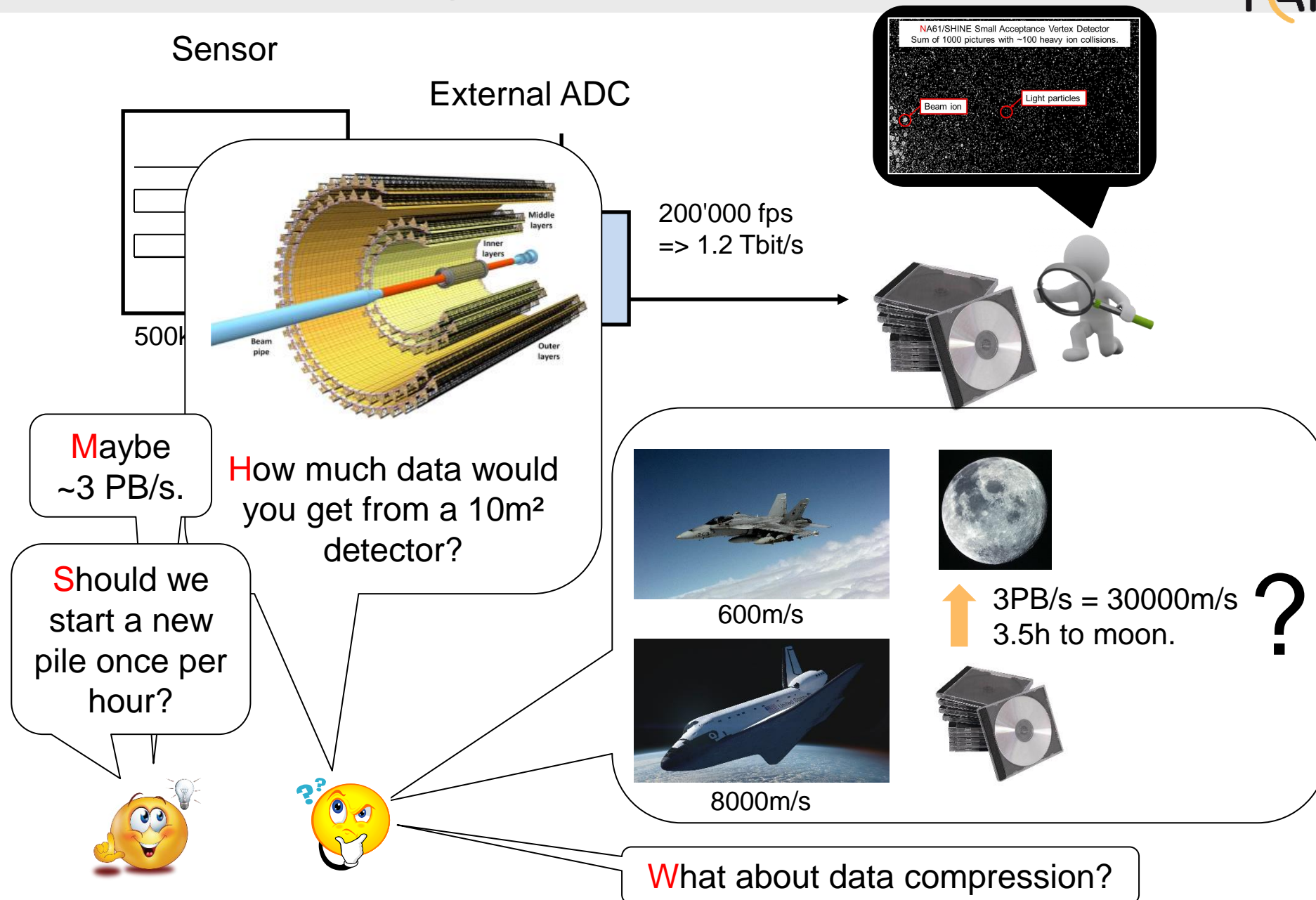


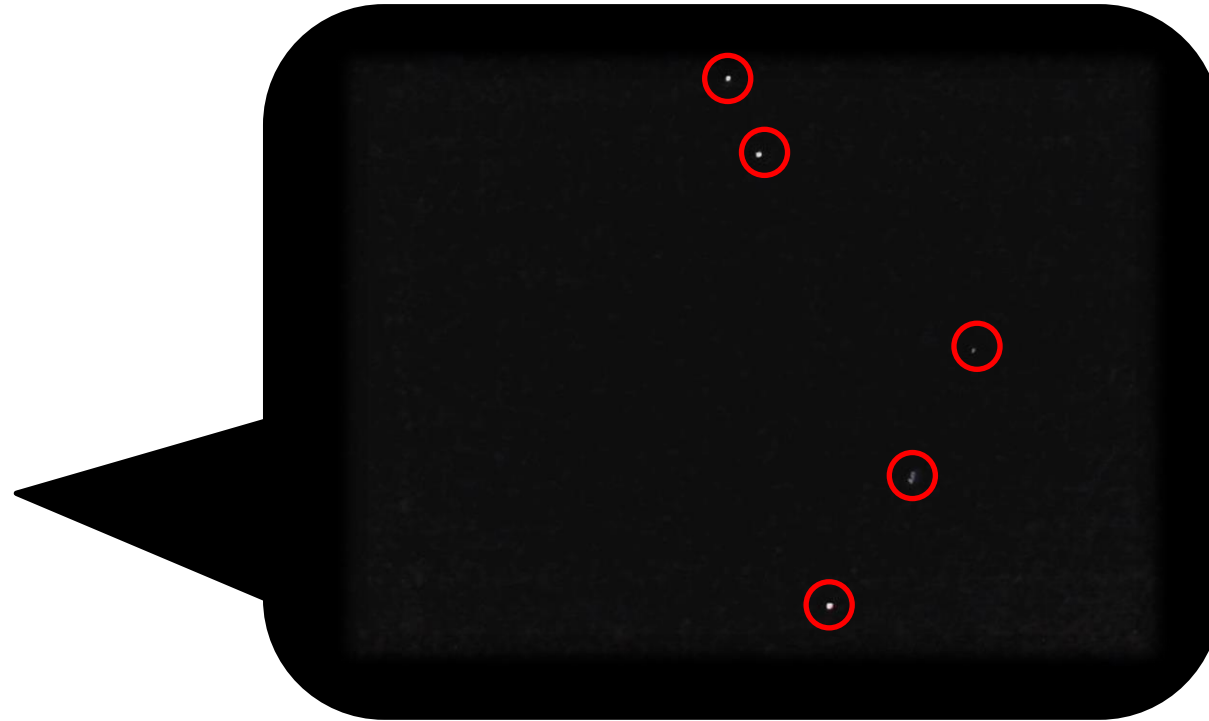
	Optimized	Traditional
Charge collection time	1 ns	100 ns

Why the gap?



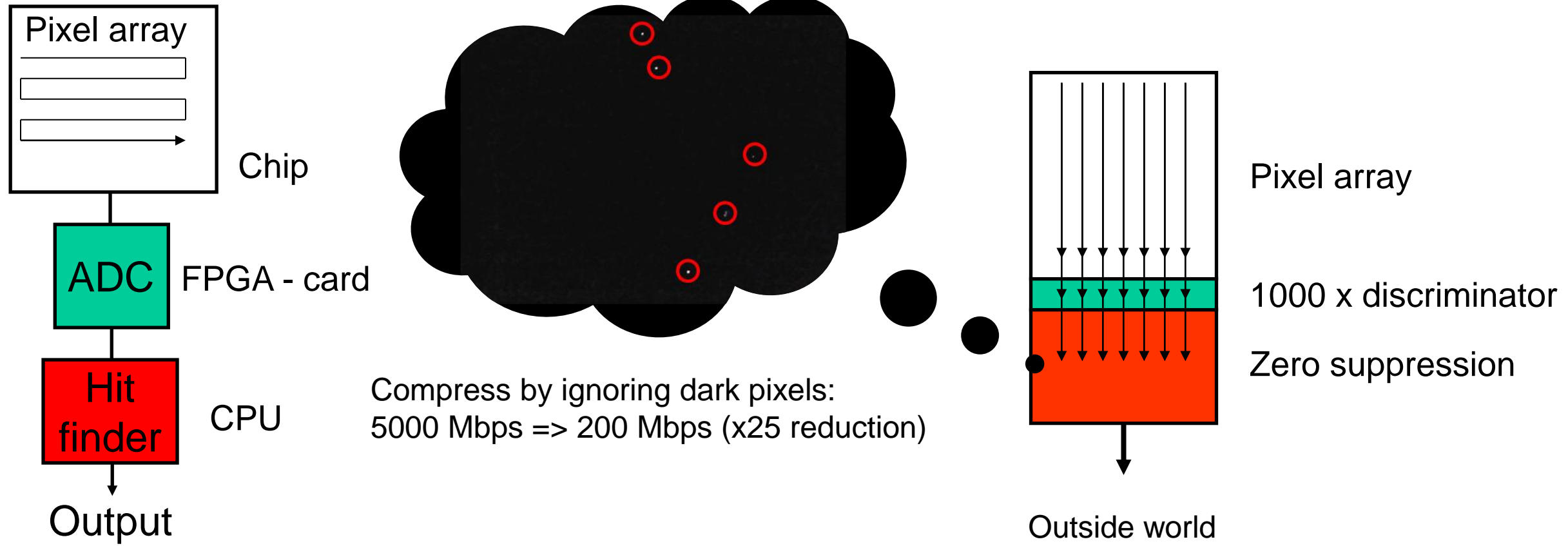
Block diagram of Gen. 1 MAPS





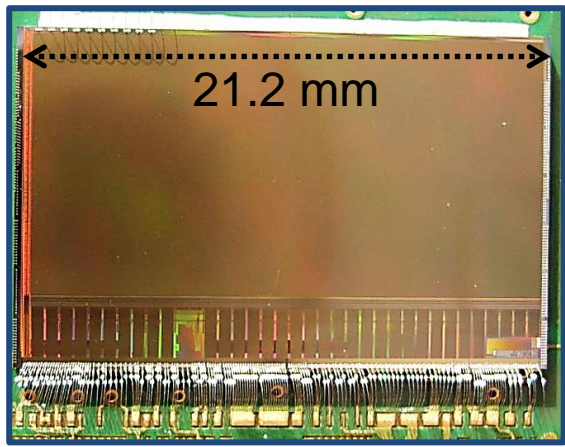
Most pixels in the frame (>99.5%) show black.
Only few pixels show white.

Idea: Ignore all black pixels.



Rolling shutter readout:
Read pixels sequentially.
Frame time: $t_{int} = \frac{N}{f} \approx \frac{10^5}{10^7 \text{ Hz}} \approx 10 \text{ ms}$

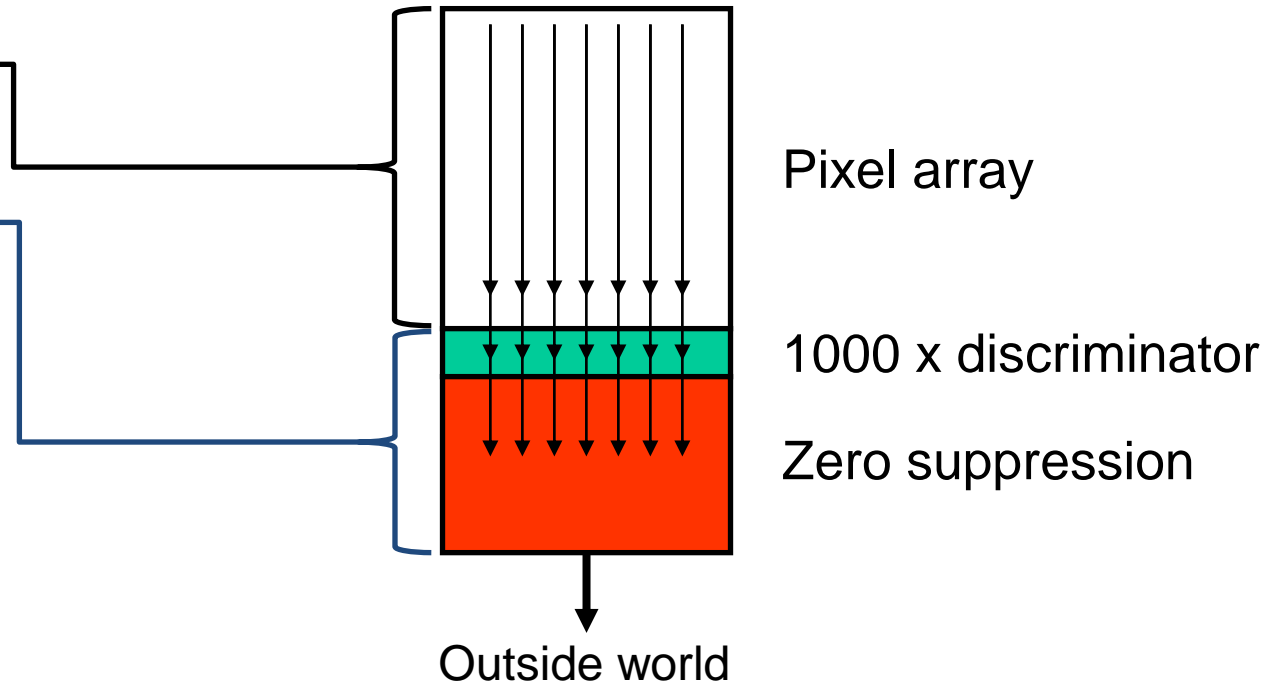
Column parallel rolling shutter readout:
Read pixels of **one column** sequentially.
Frame time: $t_{int} = \frac{N}{f} \approx \frac{10^3}{10^7 \text{ Hz}} \approx 0.1 \text{ ms}$



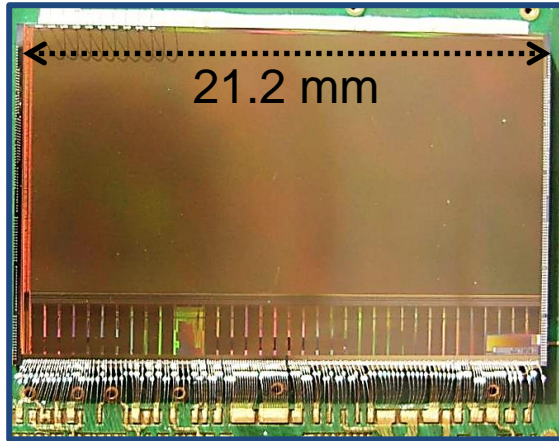
MIMOSA-26
Known from the EU-DET telescope



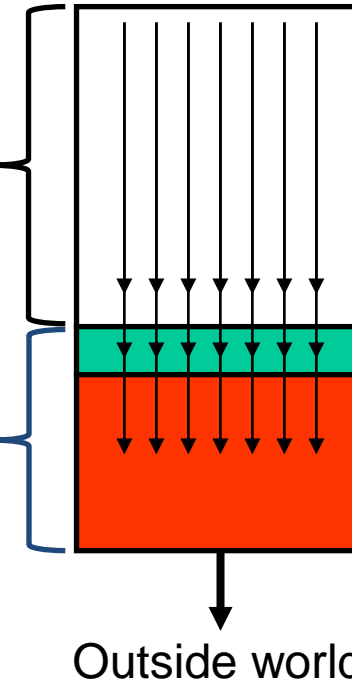
ULTIMATE (STAR-PXL detector)



Column parallel rolling shutter readout:
Read pixels of **one column** sequentially.
Frame time: $t_{int} = \frac{N}{f} \approx \frac{10^3}{10^7 \text{ Hz}} \approx 0.1 \text{ ms}$



MIMOSA-26
Known from the EU-DET telescope



Pixel array

1000 x discriminator

Zero suppression

Outside world

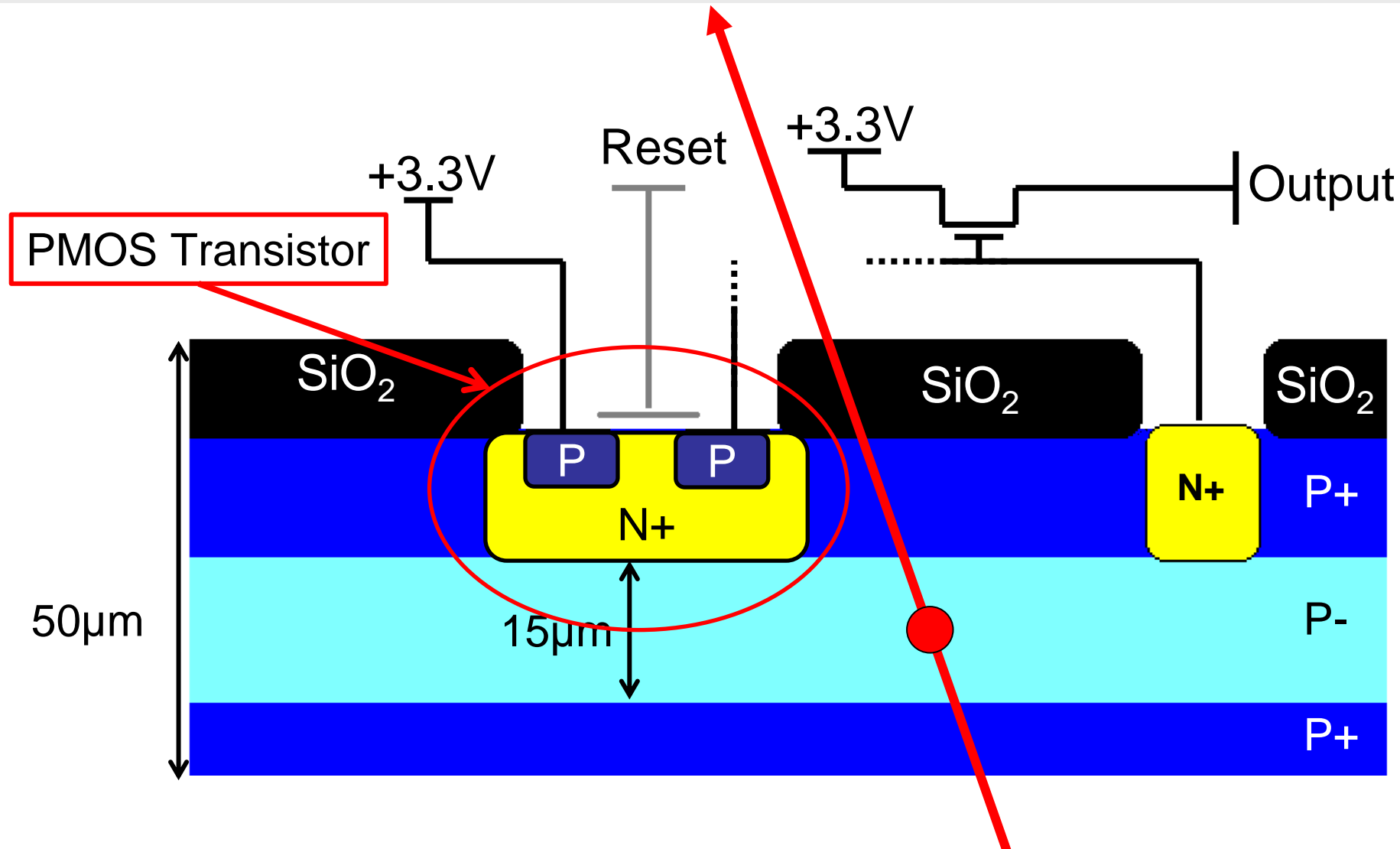
Why do you read all pixels despite this slows down things?

Because it needs in-pixel discriminators. That's not easy.

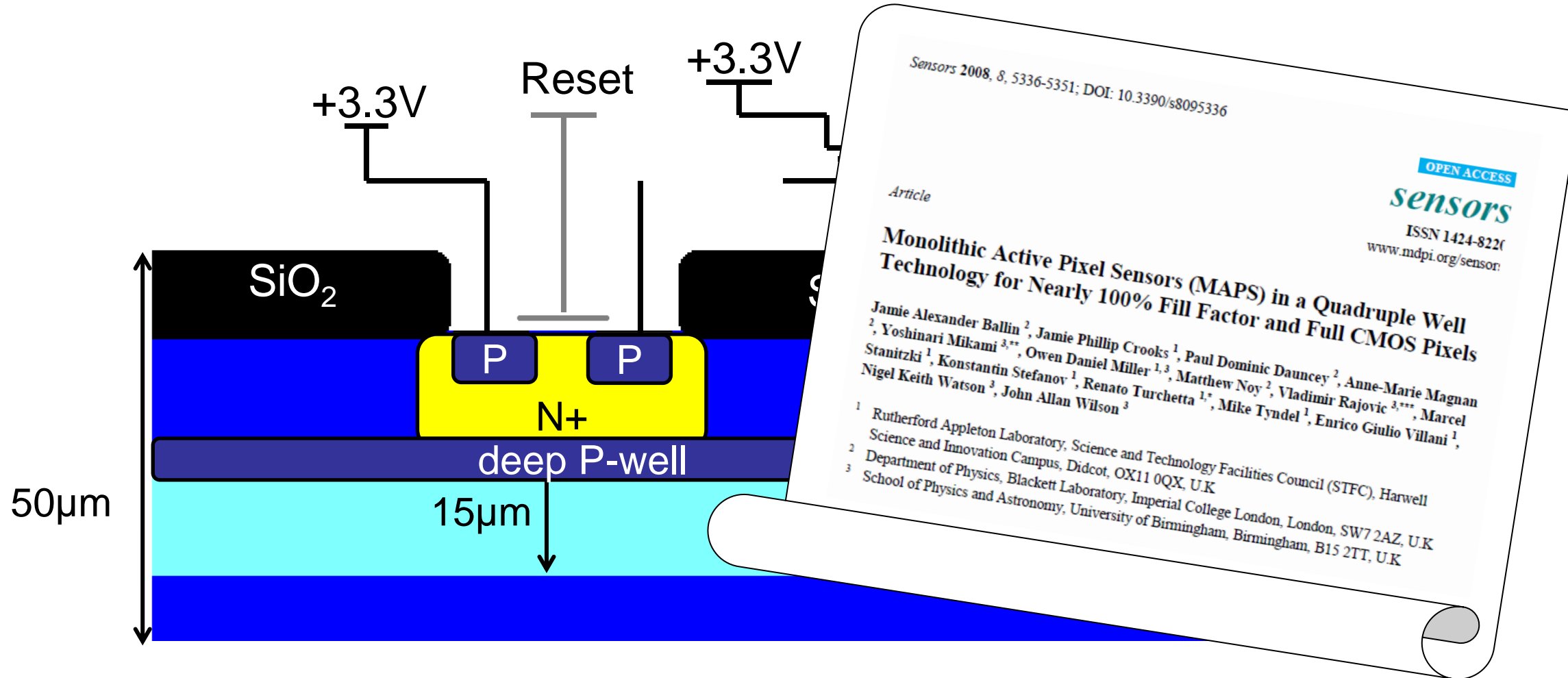


Column parallel rolling shutter readout:
Read pixels of **one column** sequentially.

$$\text{Frame time: } t_{int} = \frac{N}{f} \approx \frac{10^3}{10^7 \text{ Hz}} \approx 0.1 \text{ ms}$$



In standard CMOS sensors, no PMOS transistors are possible in pixel
 => No high level functions like discriminators ... => "slow"

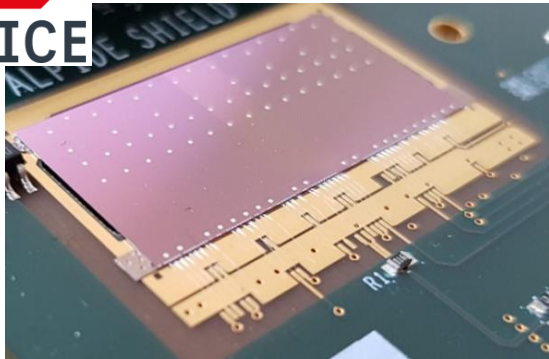


Progress was reached with Quad-well CMOS as provided by the manufacturer TowerJazz (180 nm).

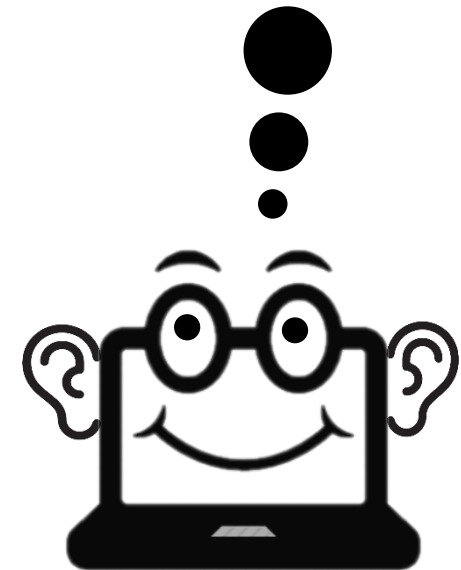
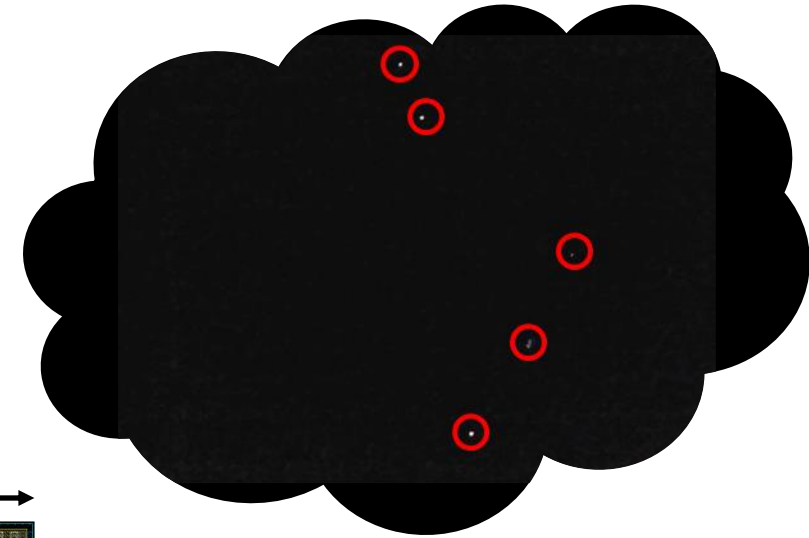
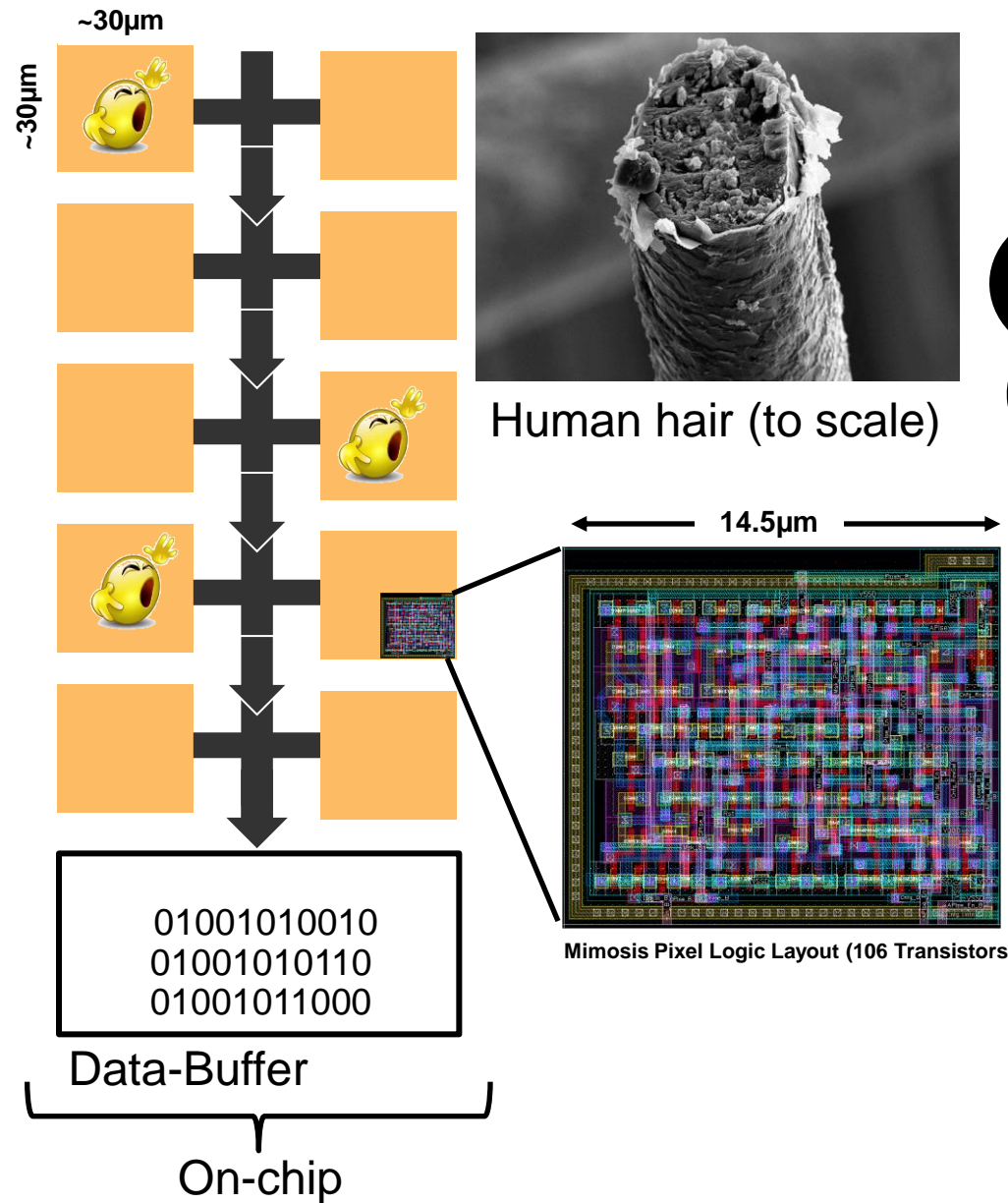
How to get the data out?



ALICE



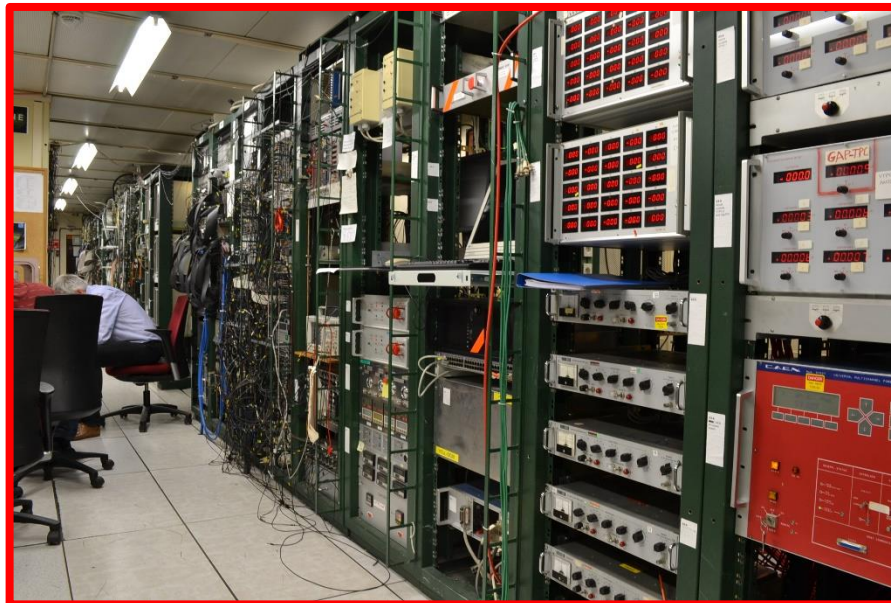
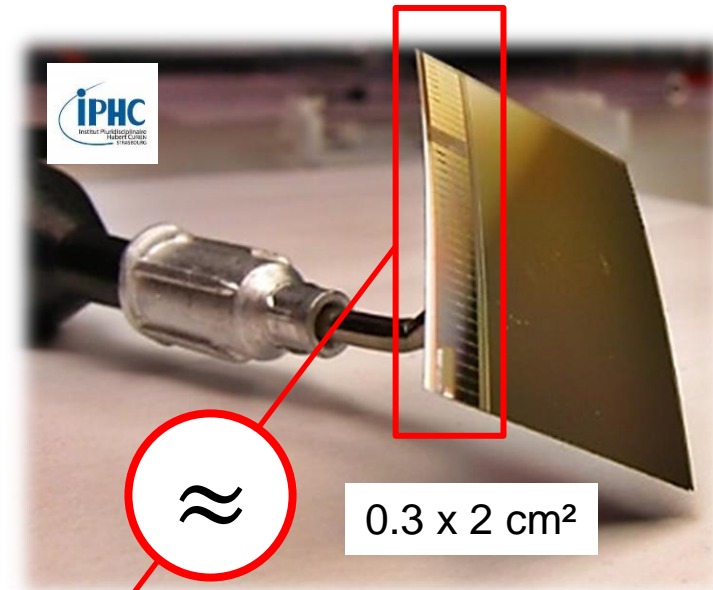
ALPIDE Sensor.
~ 50 mW/cm²



Off-chip

Side band contains:

- Data buffers.
- Voltage regulators, trim DACs.
- Slow control interface.
- Temperature sensors.
- ...



CMOS technology integrates:

- Sensors.
- Analog electronics.
- Digital data processing.

No data compression



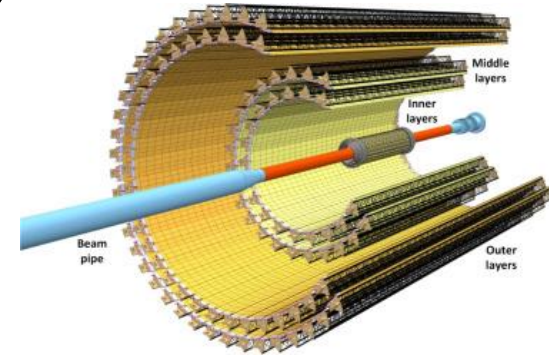
600m/s



↑ 3PB/s = 30000m/s
3.5h to moon. ?



8000m/s



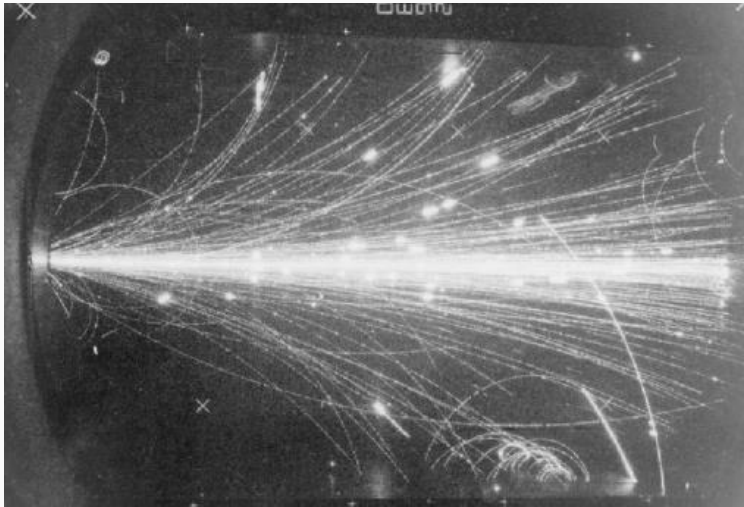
How much data would you get from a 10m² detector?

With data compression



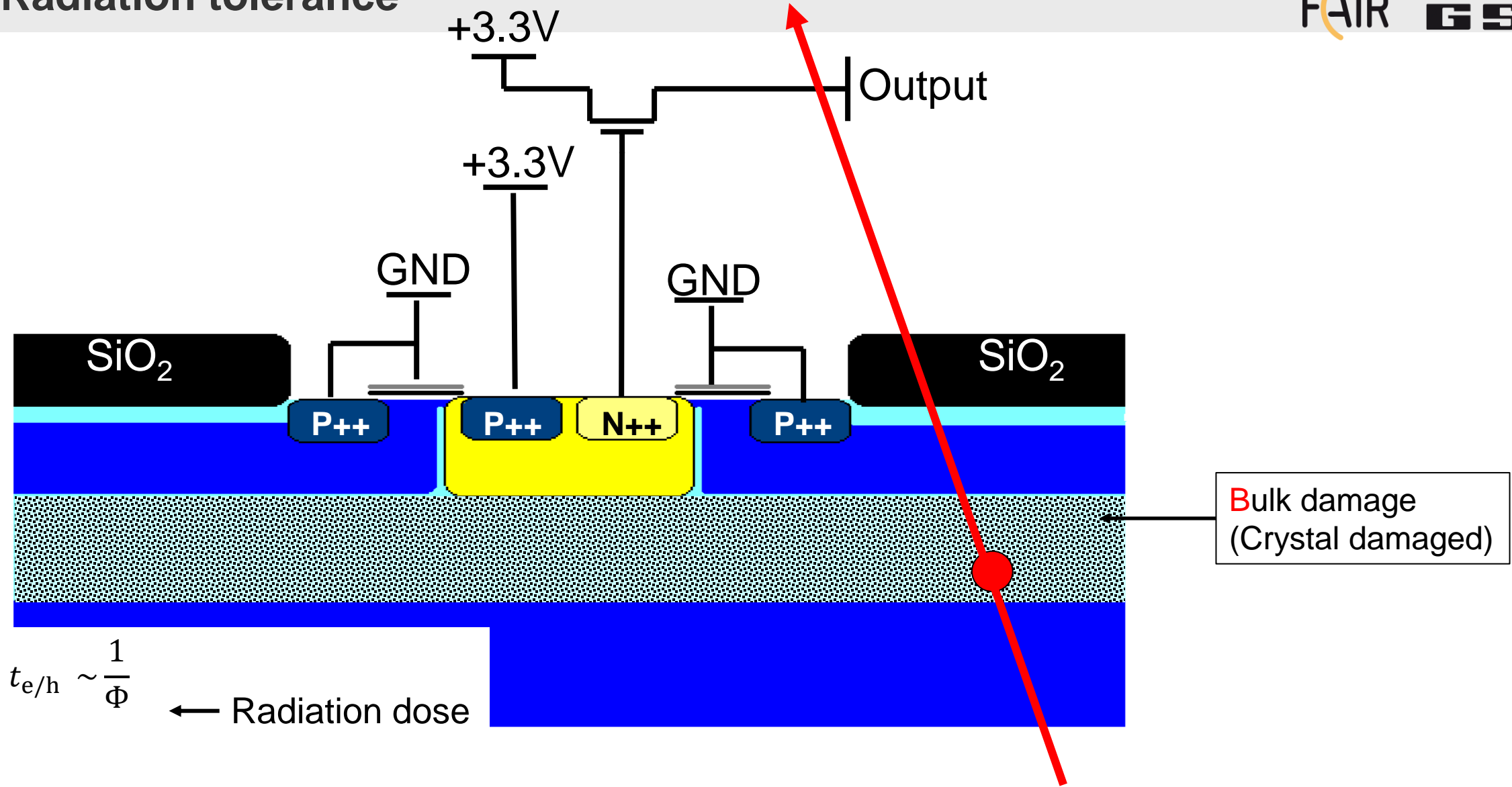
↑ ~30GB/s = 0.5 m/s





=





Initially: Charge collection by diffusion => slow => Radiation tolerance: $10^{12} n_{eq}/cm^2$
 Idea: Apply electric fields => Speed up

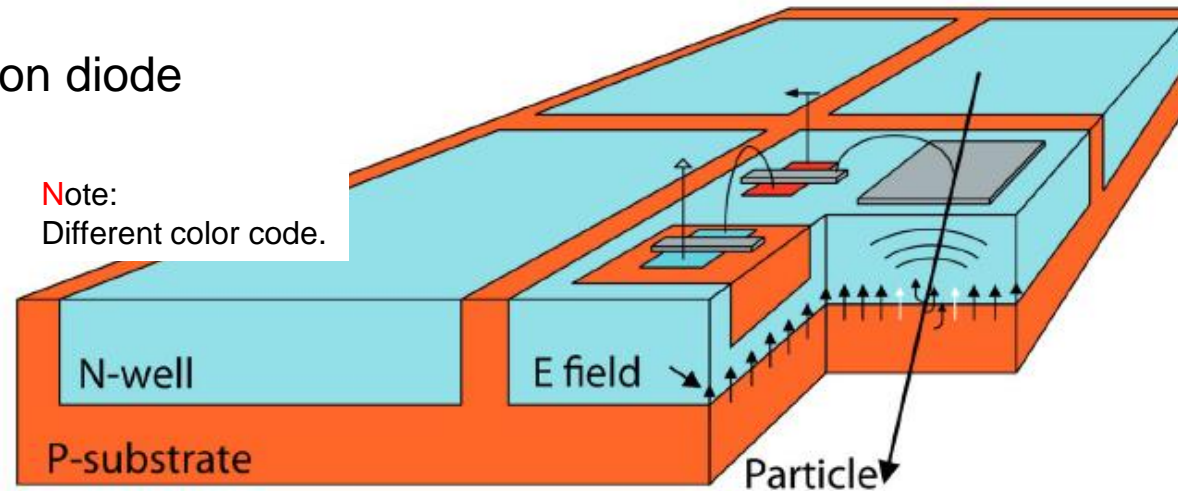
Idea:

Use "High Voltage" CMOS Process.

Embed all electronics into the collection diode

⇒ Allows for fast readout.

⇒ Allows to apply >50 V.



I.Peric, P. Fischer et al., NIM A 582 (2007) 87

Pro:

- Worked with HV – triple well process (best option at the time).
- Very fast time resolution (<10 ns) for individual hits.
- Very radiation hard due to big diodes and high voltage.

$$W = \sqrt{\frac{2 \epsilon_s (U_{bi} - U)}{e N_A}}$$

Limits:

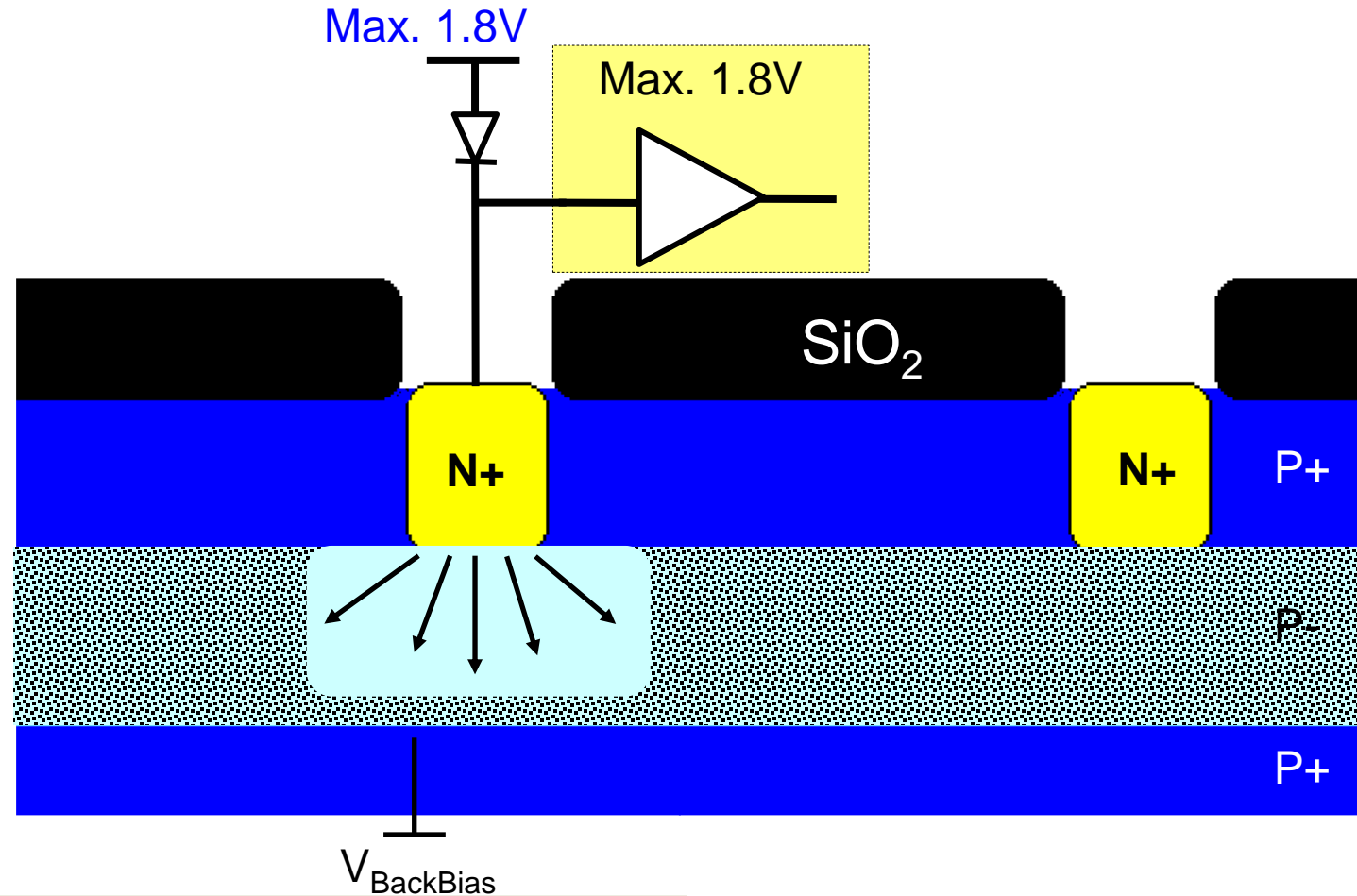
- Rather sizeable pixels (e.g. 80x80 μm^2).
- High capacitive noise.
- Relatively high power consumption.

Flat diodes:

$$W = 2 \sqrt{\frac{2 \epsilon_s (U_{bi} - U)}{e N_A}}$$

Point diodes:

$$W = 6^{(?)} \sqrt{\frac{2 \epsilon_s (U_{bi} - U)}{e N_A}}$$



Improvements

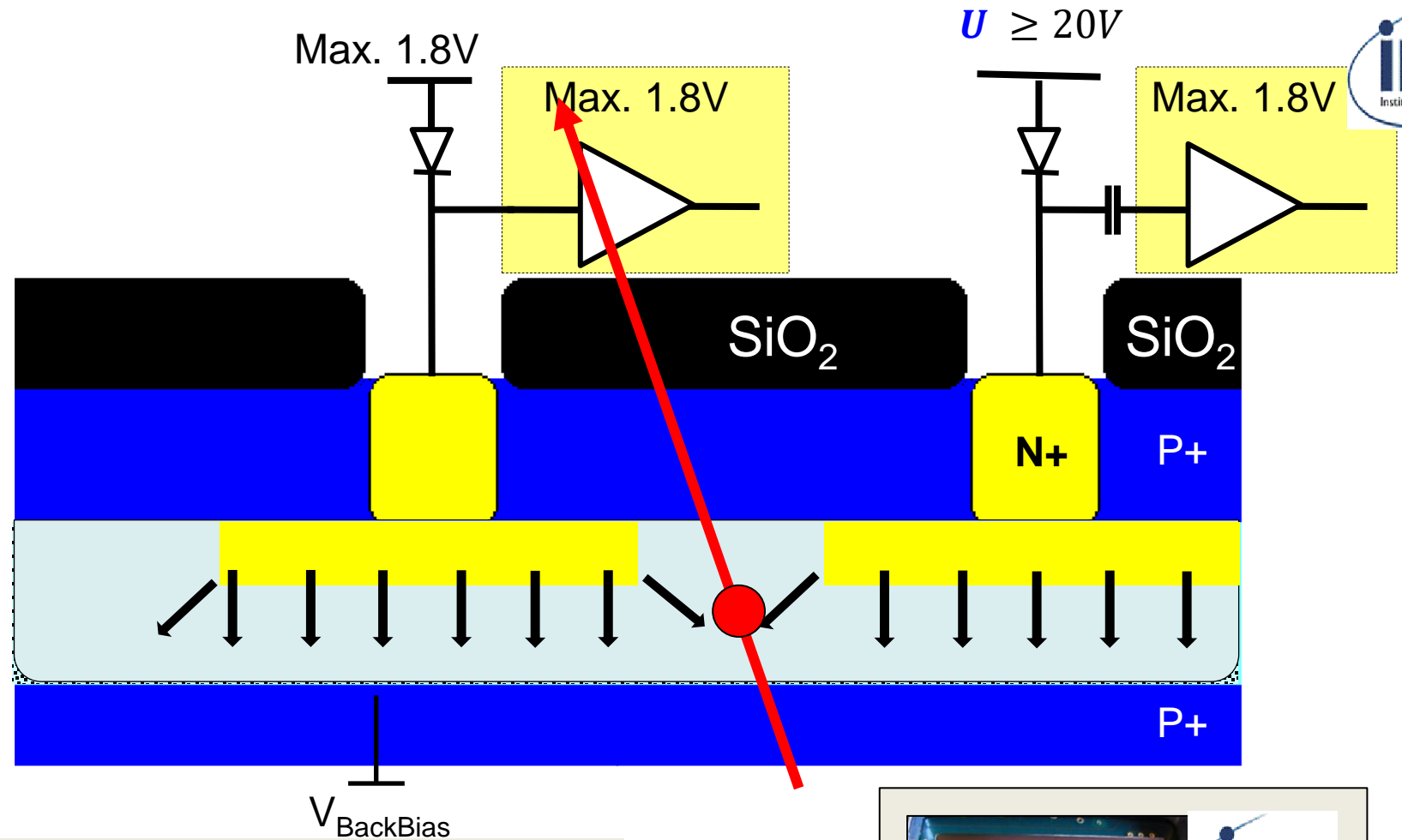
- Reduce doping, add back bias, e.g. ALPIDE (hard for >6V).

Flat diodes:

$$W = \sqrt[2]{\frac{2 \epsilon_s (U_{bi} - U)}{e N_A}}$$

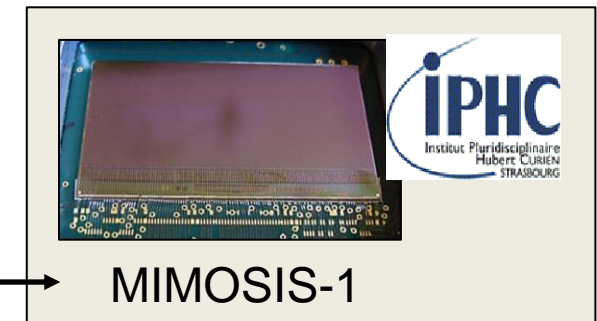
Point diodes:

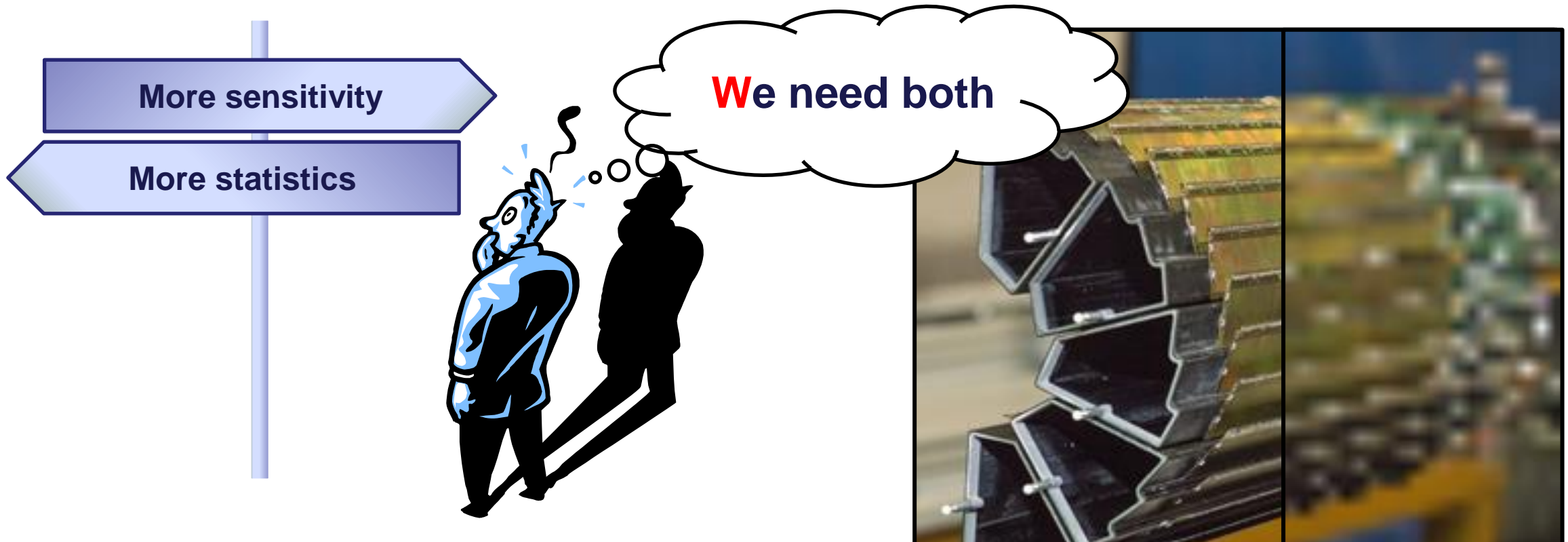
$$W = \sqrt[6^{(?) }]{\frac{2 \epsilon_s (U_{bi} - U)}{e N_A}}$$



Improvements

- Reduce doping, add back bias, e.g. ALPIDE (hard for >6V).
- Extend diodes (H. Pernegger et al., 2017 JINST 12 P06008)
- Add AC-Pixel (MIMOSIS-1)





	Hybrid pixels (2000)	MAPS (2000)	MAPS (2022)
Single point resolution	~ 30 μm	~2 μm	
Material budget	~ 500 μm Si	~ 50 μm Si	
Time resolution	25 ns	~10 ms	
Radiation hardness	~ 10^{15} $n_{\text{eq}}/\text{cm}^2$	10^{12} $n_{\text{eq}}/\text{cm}^2$	

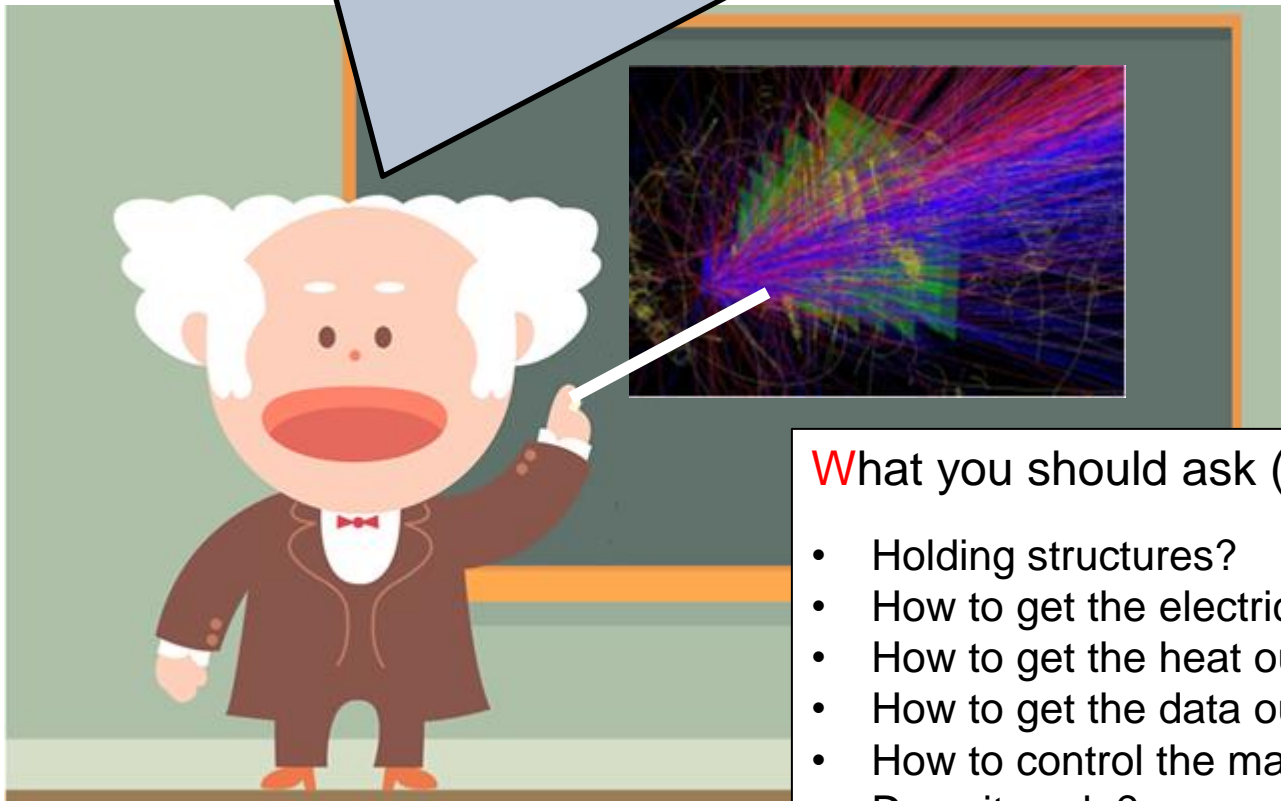
MAPS

Hybrid

→ ~10 ns (65 nm technology)

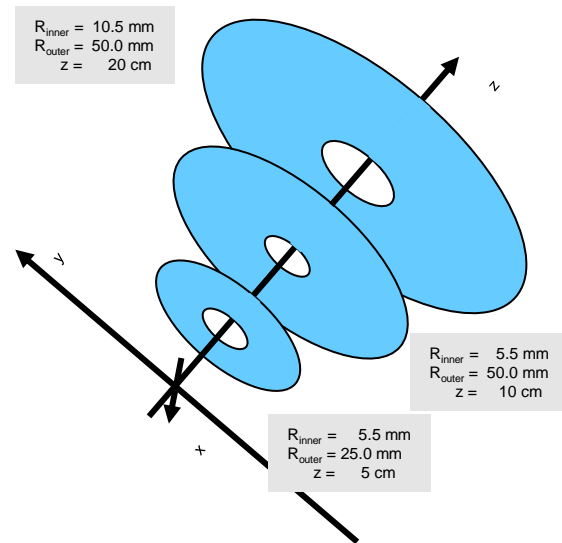
And Moore's law goes on...

Again, this structure will be fixed with the novel ***Anti Gravitation Glue™***.



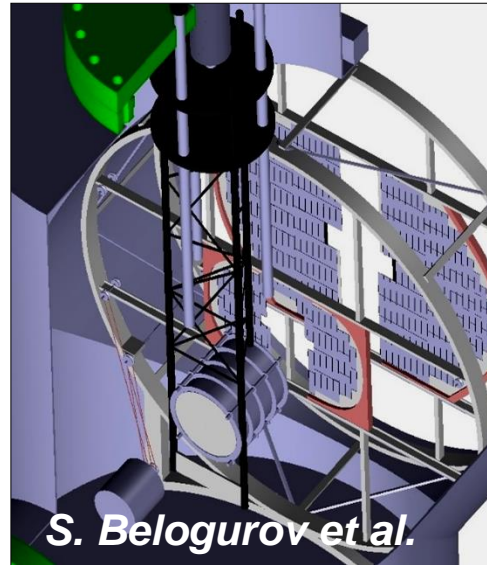
What you should ask (yourself):

- Holding structures?
- How to get the electricity in?
- How to get the heat out?
- How to get the data out (mind finite data bandwidth of cables)?
- How to control the many sensors?
- Does it scale?
- Will it tolerate radiation (no standard ICs)?



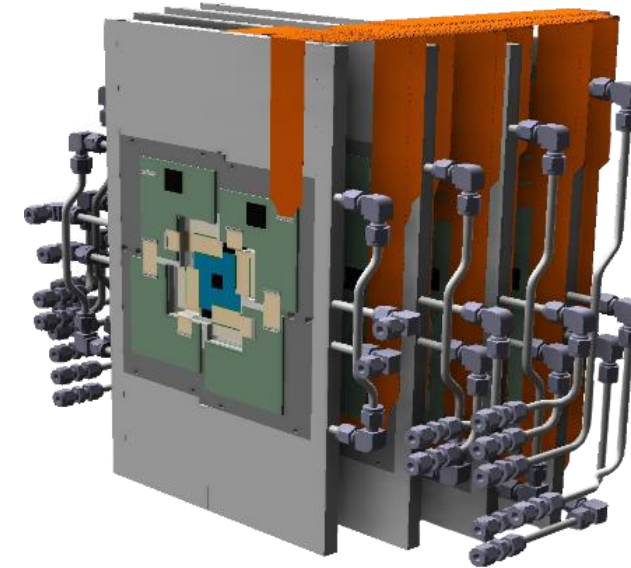
2004

- Flying disks.
- Technology unknown.
- No material estimate.



2007 (painting)

- Rough guess on technology.
- Rough guess on material.
- 2/4 stations missing.
- Simple digitizer model.



2015

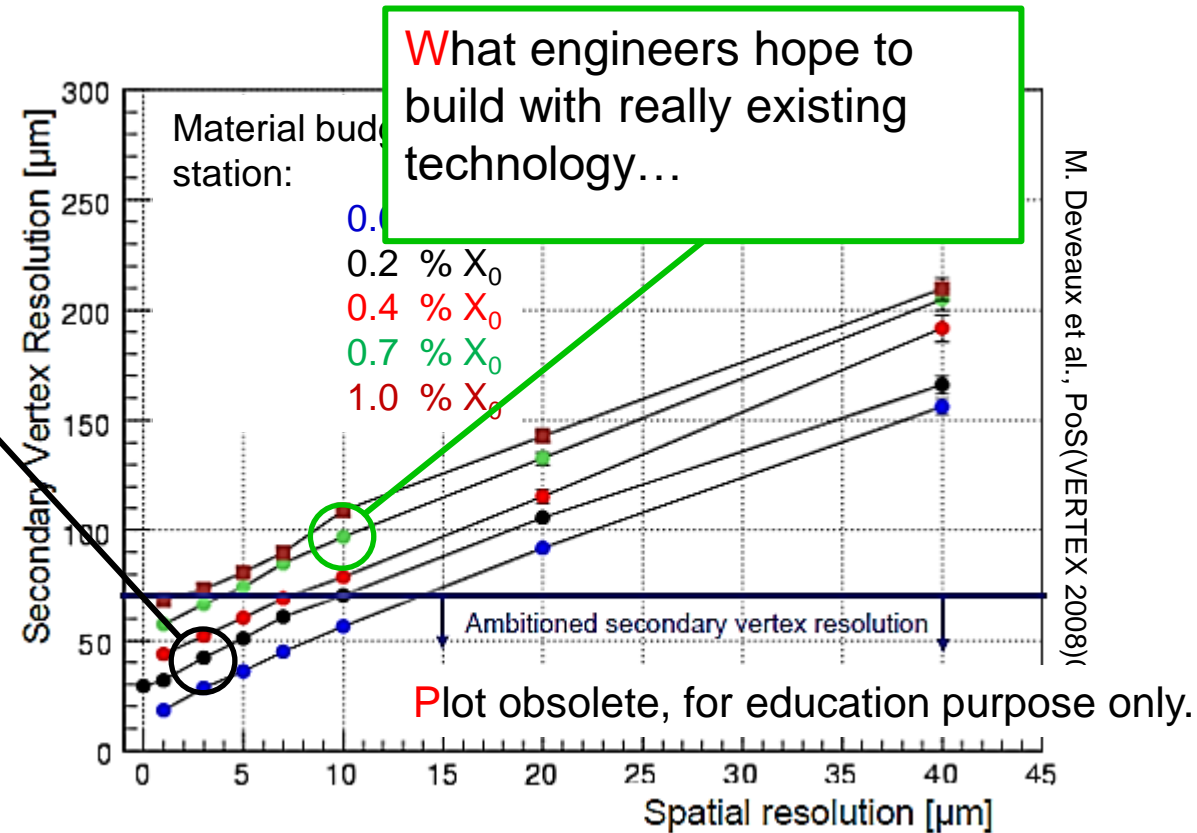
- Material gets realistic.
- Sensor models.
- 2 stations added to help tracking.

Used for many feasibility studies of CBM physics.

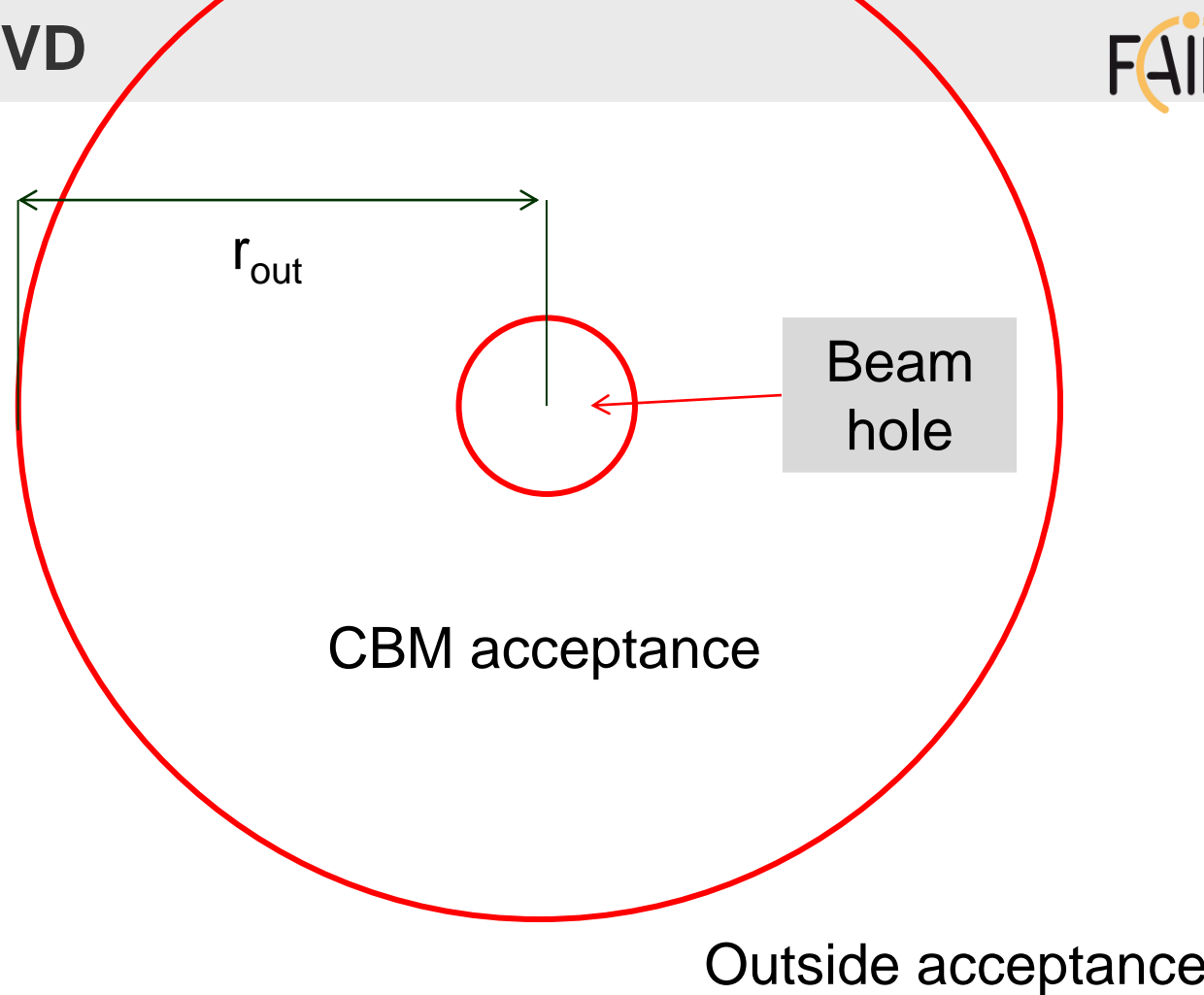
Inaccurate material may cause substantial uncertainties.

CBM - MVD – secondary vertex resolution

What physicists simulated because „we didn't know the specs of the cables yet“ ...

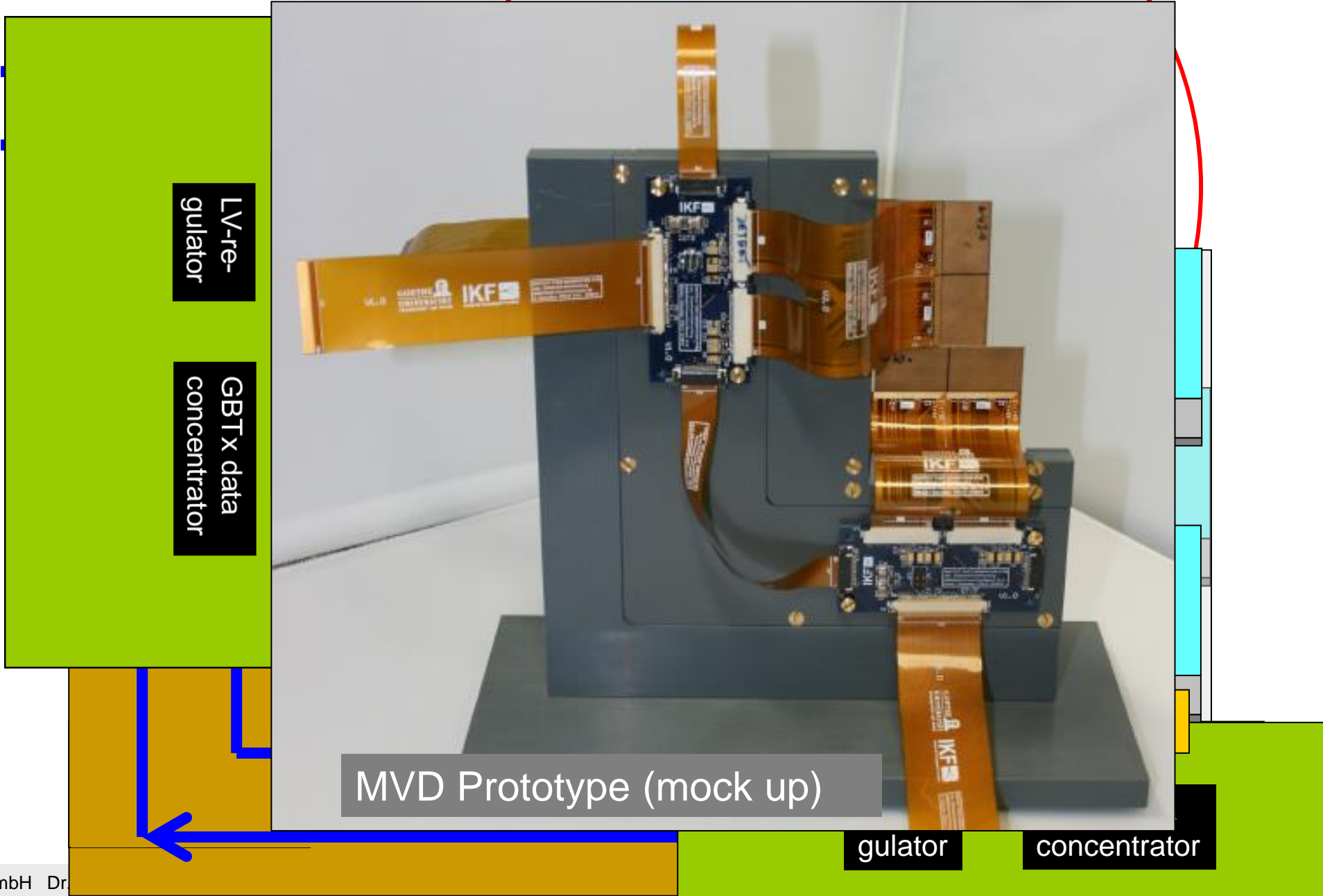


Detector material budget is dominated by the infrastructure.
Missing information turns often into too optimist physics simulations.
Remain cautions, conservative: You see what you put.



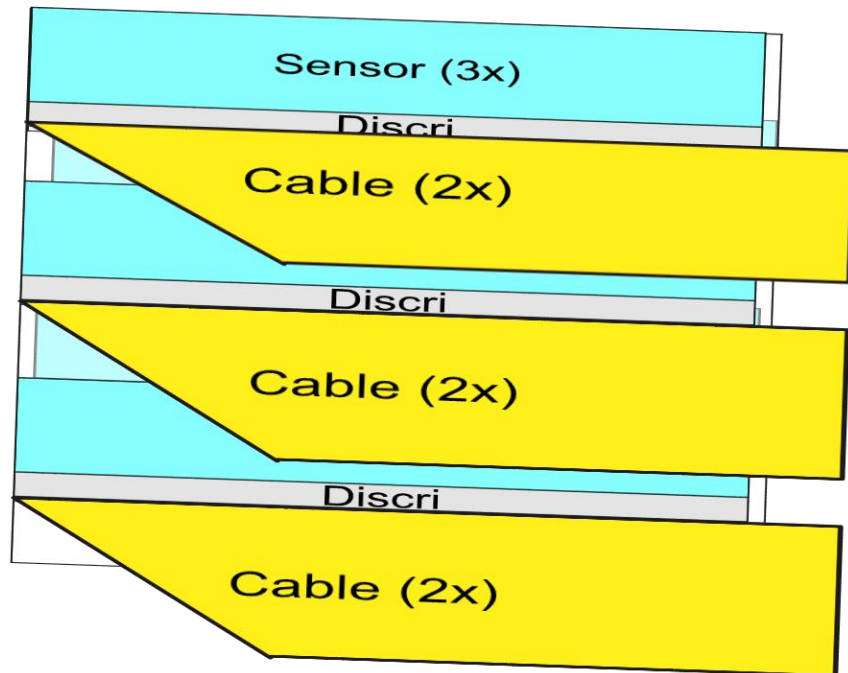
Vacuum operation requires actively cooled device.

- Use cooling support from diamond to move heat out of acceptance
- Put heat sink and FEE outside acceptance



PRESTO:

Prototype of a quarter station incl. sensors (MIMOSA-26), cables, support etc.

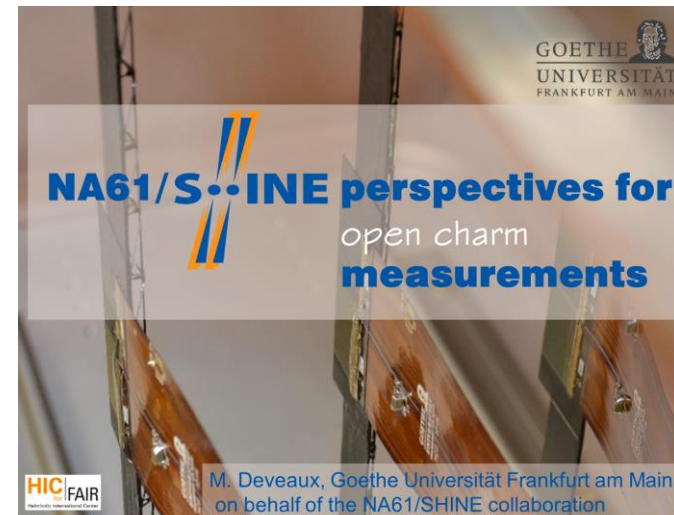


Integration completed. Test:

- Vacuum compatibility
- Temperature cycling
- ...



(More than) A spin-off:

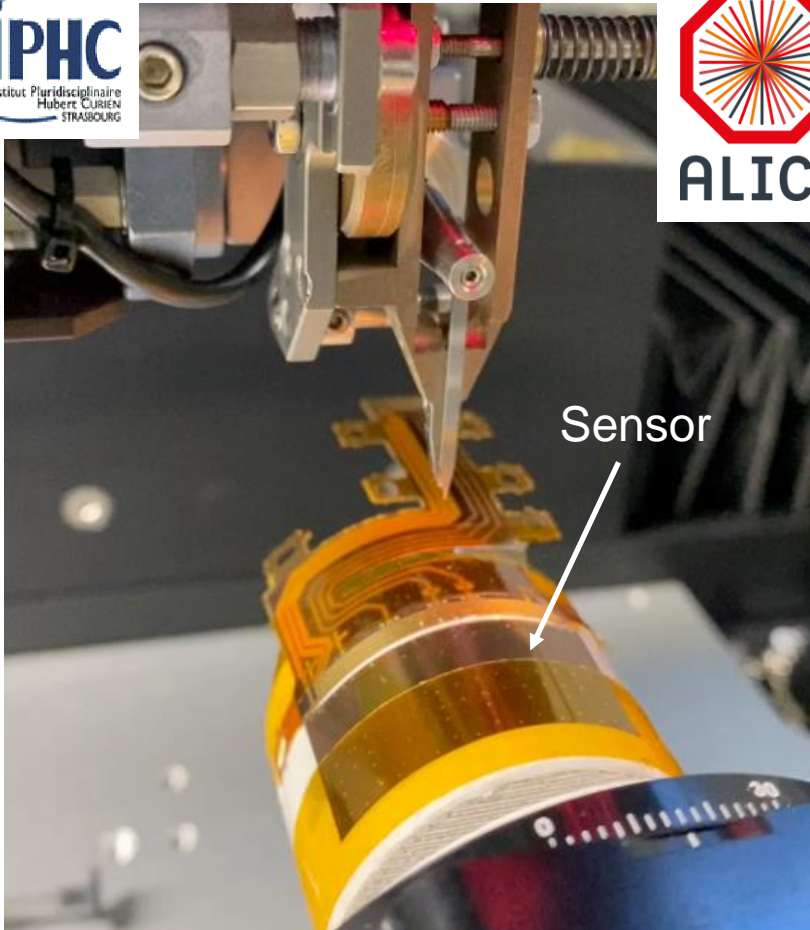


The NA61/SHINE vertex detector uses (and tests) MVD prototype/PRESTO electronics

M. Deveaux for NA61/SHINE,
SQM2017, Utrecht, Netherlands



ALICE



ALICE ITS-3 program:
Curved – Wafer detectors



CMOS Monolithic Active Pixel Sensors

- Show lowest material budget together with highest granularity.
- Integrate pixels and electronics on one system-on-a-chip.
- Can be mass produced with industrial CMOS processes at low cost.

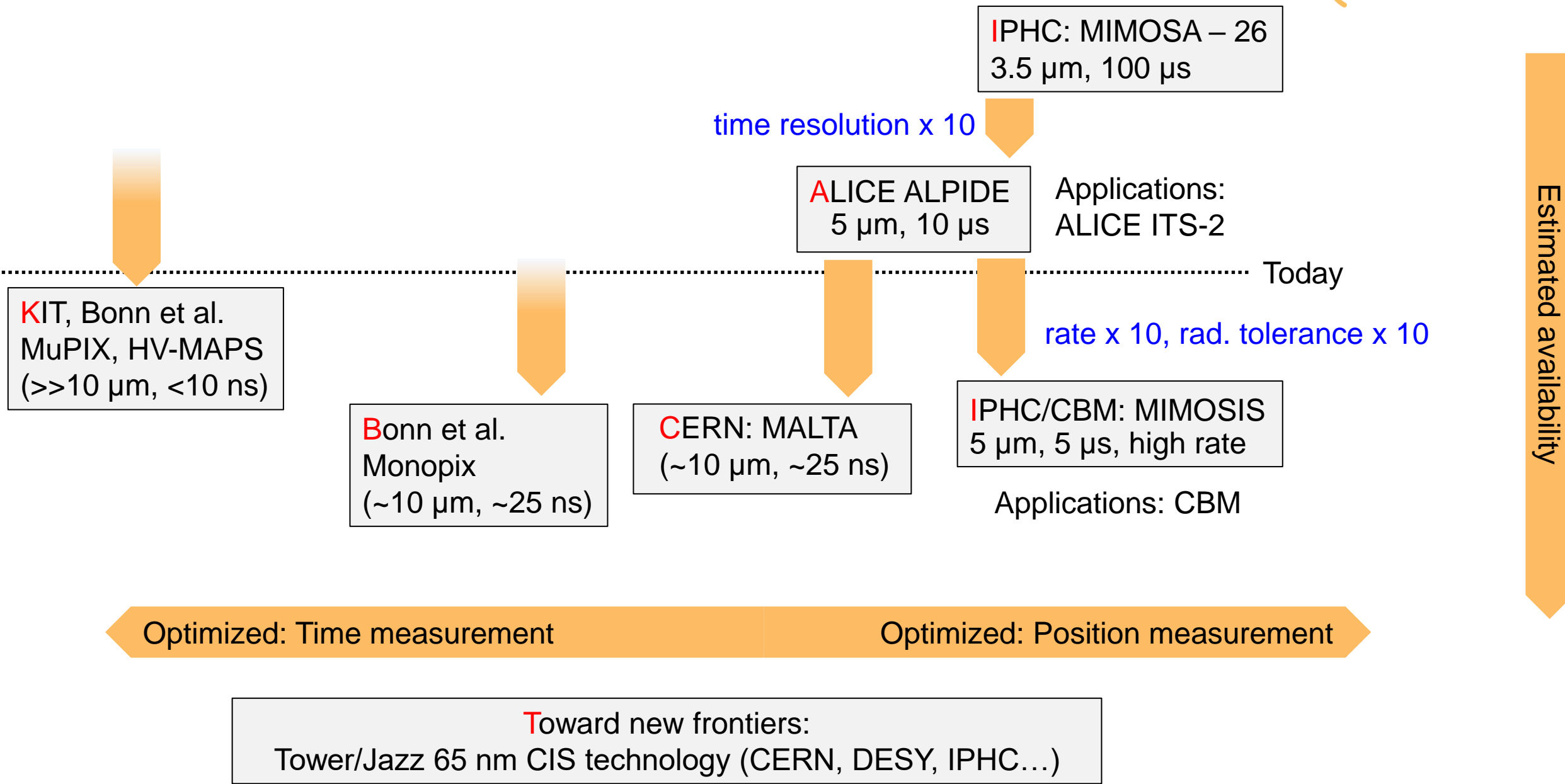
- Are the coolest detectors ever made (my biased personal opinion).

When building detectors, consider that:

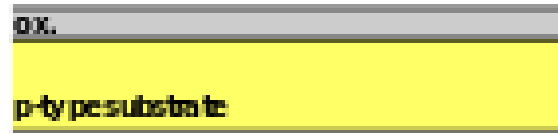
- the material budget and performance of detectors is determined by infrastructure.
 - ⇒ Optimizing sensors wins the battle, optimizing cables and cooling wins the war.

- Being too optimist in simulations is mostly self-cheating.
 - ⇒ Try to be conservative if you are missing detailed knowledge.

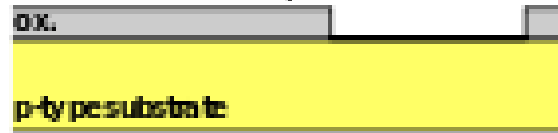
The performance of MAPS was improved by a factor 1000 during the past 20 years...
... and the story has just started.



1. Grow field oxide



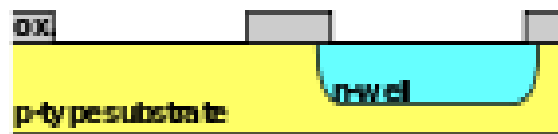
2. Etch oxide for pMOSFET



3. Diffuse n-well



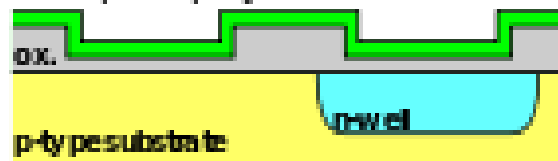
4. Etch oxide for nMOSFET



5. Grow gate oxide



6. Deposit polysilicon



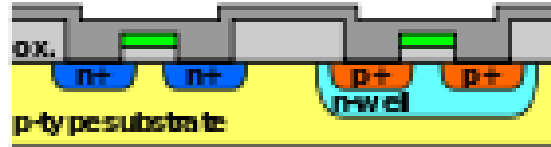
7. Etch polysilicon and oxide



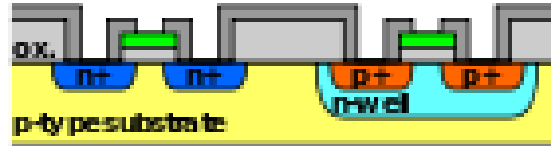
8. Implant sources and drains



9. Grow nitride



10. Etch nitride



11. Deposit metal



12. Etch metal



CMOS production:

- Is highly complex (special companies needed).
- Works with lithography.
- Needs ~ 20 – 30 masks for modern processes.